

# MAPS R&D for tracking and calorimetry at future e<sup>+</sup>e<sup>-</sup> colliders

---

**Caterina Vernieri**

Christos Bakalis, James E. Brau, Martin Breidenbach, Angelo Dragone, Christopher Kenney, Alexandre Habib, Lorenzo Rota, Julie Segal, Mirella Vassilev

*April 26, 2024*

# Current benchmarks and next steps

The goal of measuring Higgs properties with sub-% precision translates into ambitious requirements for detectors at e+e-

Initial state	Physics goal	Detector	Requirement
$e^+e^-$	$hZZ$ sub-%	Tracker  Calorimeter	$\sigma_{p_T}/p_T=0.2\%$ for $p_T < 100$ GeV $\sigma_{p_T}/p_T^2 = 2 \cdot 10^{-5} / \text{GeV}$ for $p_T > 100$ GeV 4% particle flow jet resolution EM cells $0.5 \times 0.5 \text{ cm}^2$ , HAD cells $1 \times 1 \text{ cm}^2$ EM $\sigma_E/E = 10\%/\sqrt{E} \oplus 1\%$ shower timing resolution 10 ps
	$hb\bar{b}/hc\bar{c}$	Tracker	$\sigma_{r\phi} = 5 \oplus 15(p \sin \theta^{\frac{3}{2}})^{-1} \mu\text{m}$ 5 $\mu\text{m}$ single hit resolution

[Arxiv:2209.14111](https://arxiv.org/abs/2209.14111) [Arxiv:2211.11084](https://arxiv.org/abs/2211.11084) [DOE Basic Research Needs Study on Instrumentation](#)

# Current benchmarks and next steps

The goal of measuring Higgs properties with sub-% precision translates into ambitious requirements for detectors at e+e-

Initial state	Physics goal	Detector	Requirement
$e^+e^-$	$hZZ$ sub-%	Tracker  Calorimeter	$\sigma_{p_T}/p_T=0.2\%$ for $p_T < 100$ GeV $\sigma_{p_T}/p_T^2 = 2 \cdot 10^{-5} / \text{GeV}$ for $p_T > 100$ GeV 4% particle flow jet resolution EM cells $0.5 \times 0.5 \text{ cm}^2$ , HAD cells $1 \times 1 \text{ cm}^2$ EM $\sigma_E/E = 10\%/\sqrt{E} \oplus 1\%$ shower timing resolution 10 ps
	$hb\bar{b}/hc\bar{c}$	Tracker	$\sigma_{r\phi} = 5 \oplus 15(p \sin \theta^{\frac{3}{2}})^{-1} \mu\text{m}$ 5 $\mu\text{m}$ single hit resolution

[Arxiv:2209.14111](https://arxiv.org/abs/2209.14111) [Arxiv:2211.11084](https://arxiv.org/abs/2211.11084) [DOE Basic Research Needs Study on Instrumentation](#)

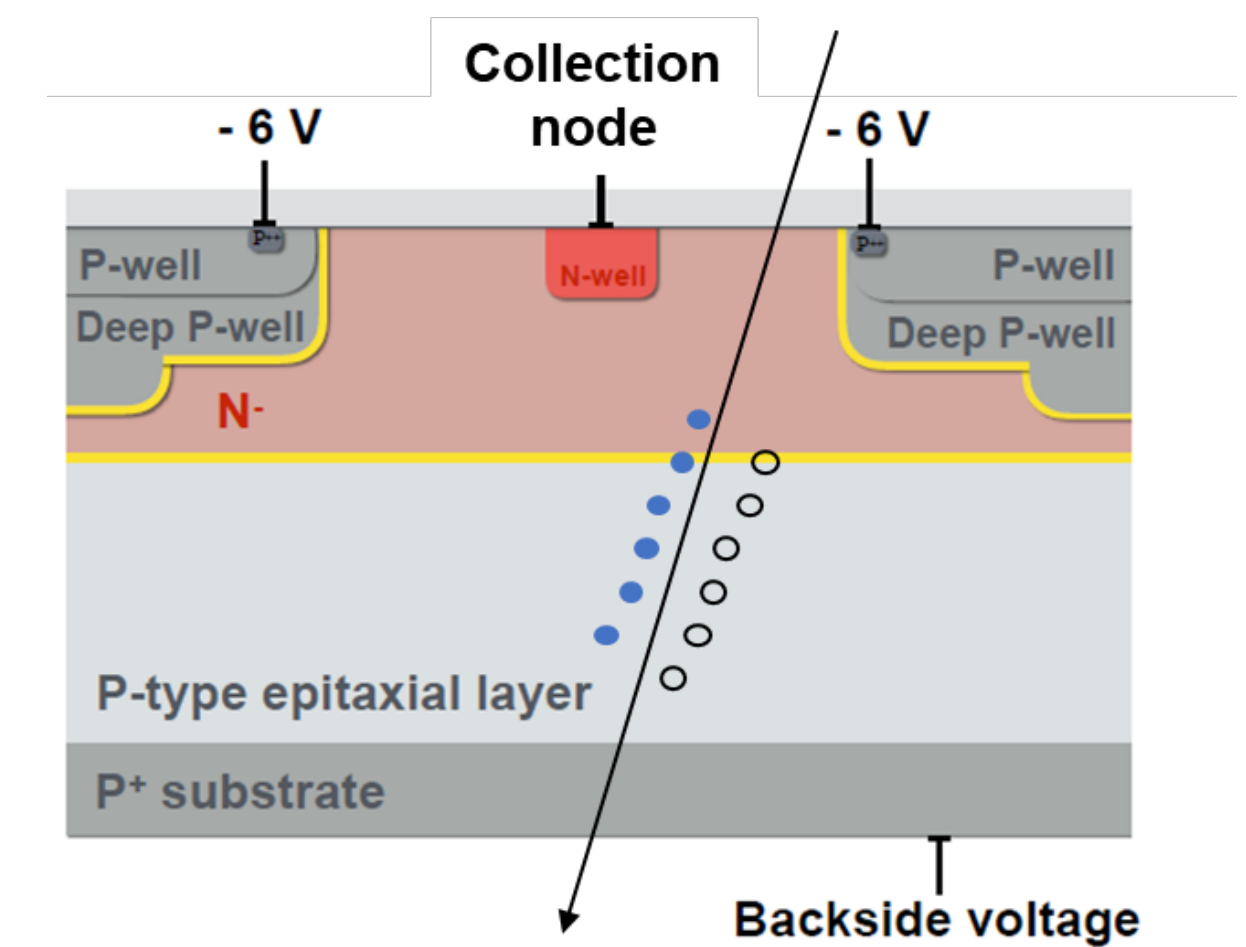
- Requirements mostly driven by (Higgs) specific benchmarks
- Technological advances can open new opportunities and additional physics benchmarks (i.e.  $H \rightarrow ss$ ) can add more stringent requirements

**Focus topics for the ECFA study on Higgs / Top / EW factories *should* provide further detector design guidelines ([2401.07564](#)) by Spring 2025**

# Monolithic Active Pixel Sensors - MAPS

A suitable technology for high precision tracker and high granularity calorimetry

- Monolithic technologies can yield to higher granularity, thinner, intelligent detectors at lower overall cost
- Significantly lower material budget: sensors and readout electronics are integrated on the same chip
  - Eliminate the need for bump bonding : thinned to less to  $50\mu\text{m}$
  - Smaller pixel size, not limited by bump bonding ( $<25\mu\text{m}$ )
  - Lower costs : implemented in standard commercial CMOS processes technologies with small feature size (65-110 nm)
    - Either reduce power consumption or add more features
- Target big sensors (up to wafer size) through use of “stitching” (step-and-repeat of reticles) to reduce further the overall material budget



**Current sensor optimization in  
TJ180/TJ65 nm process  
Effort to identify US foundry on going**

Snowmass White Paper [2203.07626](#)  
Common US R&D initiative for future  
Higgs Factories [2306.13567](#)

# Current effort



## Co-design approach: close interaction between physics studies and technology R&D [4]

- Novel CMOS process for MAPS has recently become available, CERN (WP1.2 Collaboration) provides access to scientific community: TowerJazz-Panasonic (TPSCO) 65 nm CMOS imaging process with modified implants
- Builds on sensor optimization done for the TJ180 process<sup>[1-2]</sup>, excellent charge collection efficiency and low capacitance <sup>[3]</sup>
  - Increased density for circuits: Higher spatial resolution, better timing performance at same power consumption.
- Supports stitching: enable wafer-scale MAPS → **potential to greatly reduce costs of future experiments**
- ALICE ITS3 upgrade is the main driver of CERN WP1.2 efforts
- SLAC is the only US institute involved in Engineering Runs fabrication
- Several challenges towards wafer-scale devices → **large international effort needed to address all of them**
- Large collaboration is interested in designing solutions for power distribution compatible with stitching and enabling O(ns) timing precision

[1] M. van Rijnbach *et al.*, *Radiation hardness and timing performance in MALTA monolithic pixel sensors in TowerJazz 180 nm*, 2022 JINST C04034

[2] M. Munker *et al.*, *Simulations of CMOS pixel sensors with a small collection electrode, improved for a faster charge collection and increased radiation tolerance*, 2019 JINST 14C05013

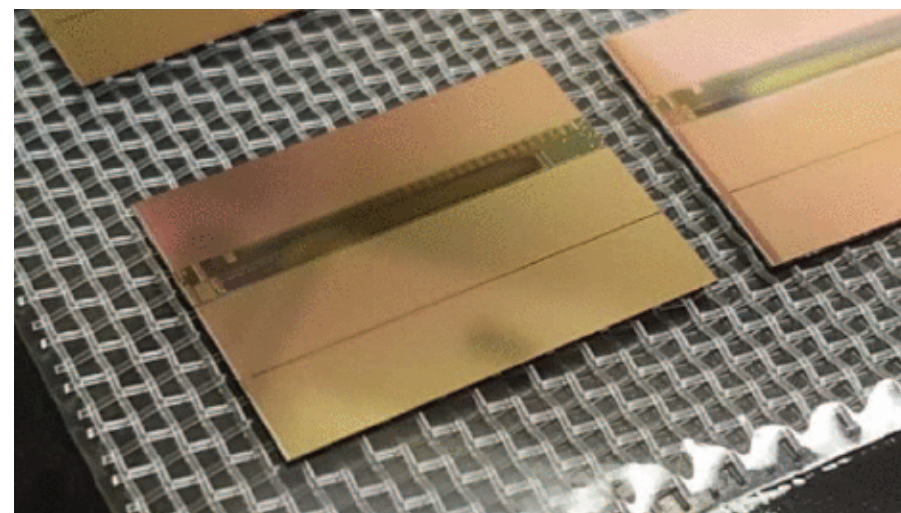
[3] S. Bugiel *et al.*, *Charge sensing properties of monolithic CMOS pixel sensors fabricated in a 65 nm technology*, NIMA Volume 1040, 1 October 2022, 167213

[4] J. E. Brau *et al.*, *The SiD Digital ECal based on Monolithic Active Pixel Sensors*, <https://agenda.linearcollider.org/event/9211/sessions/5248>, 2021.

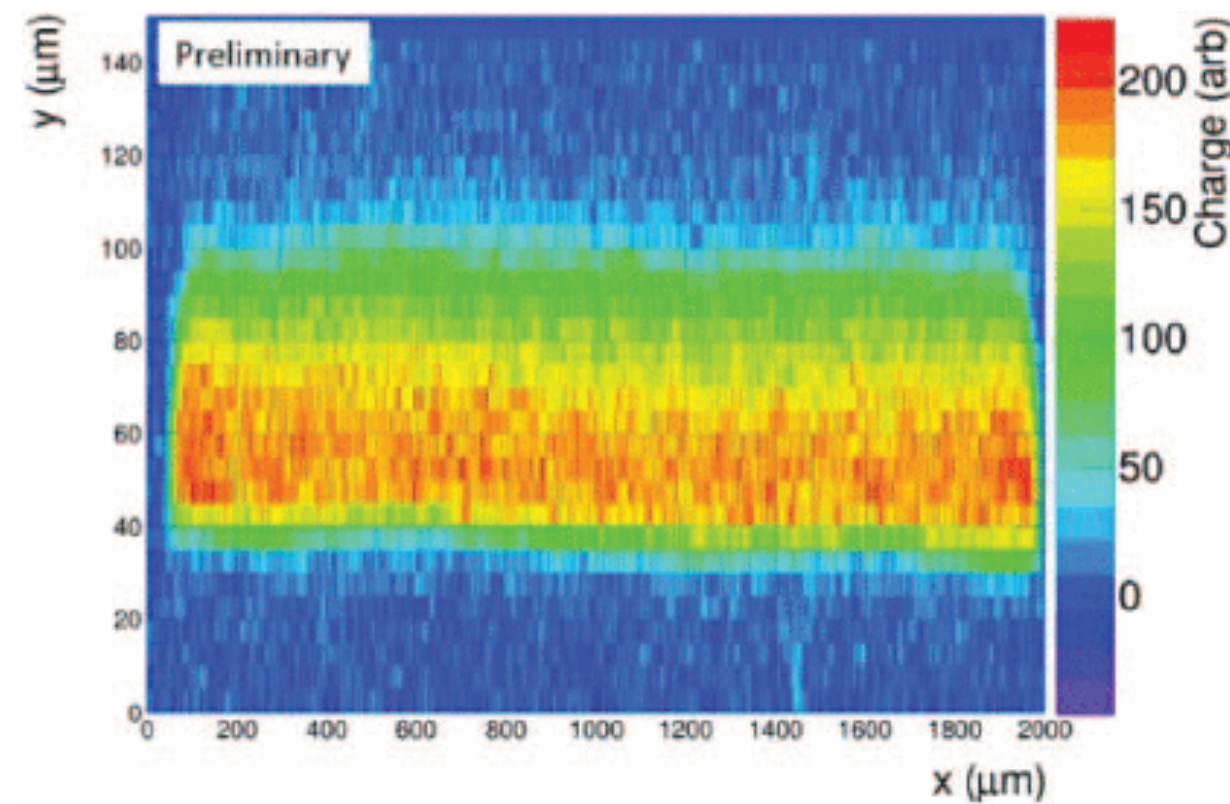
# Large area MAPS – SLAC expertise

- SLAC has many years of experience in MAPS, developed detectors in several technologies<sup>[1-4]</sup>
- MAPS developments leverage large synergy with other core mission at SLAC: X-ray detectors (BES)
- Two most recent examples:

## CHES-II (AMS-350nm): prototype for strip detector for ATLAS

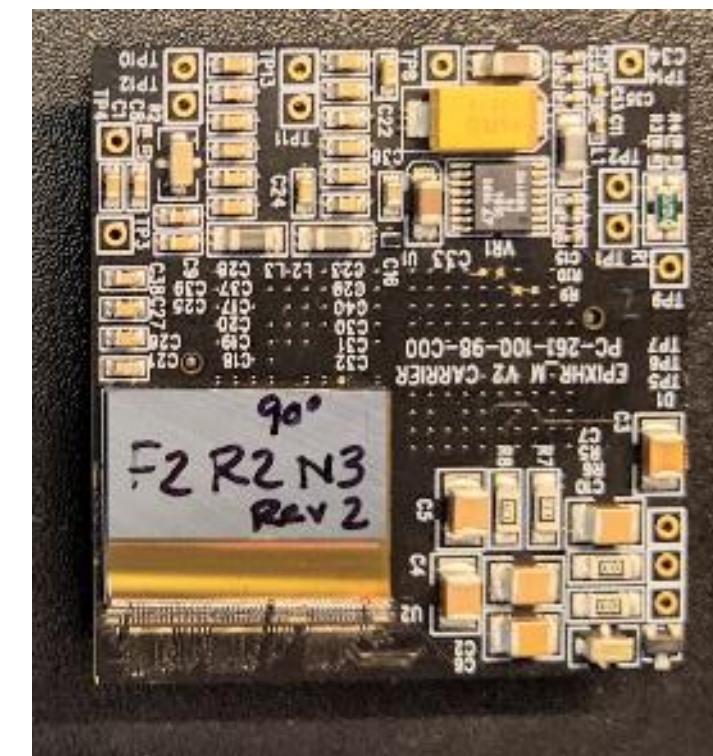


Photograph of the CHES-II die

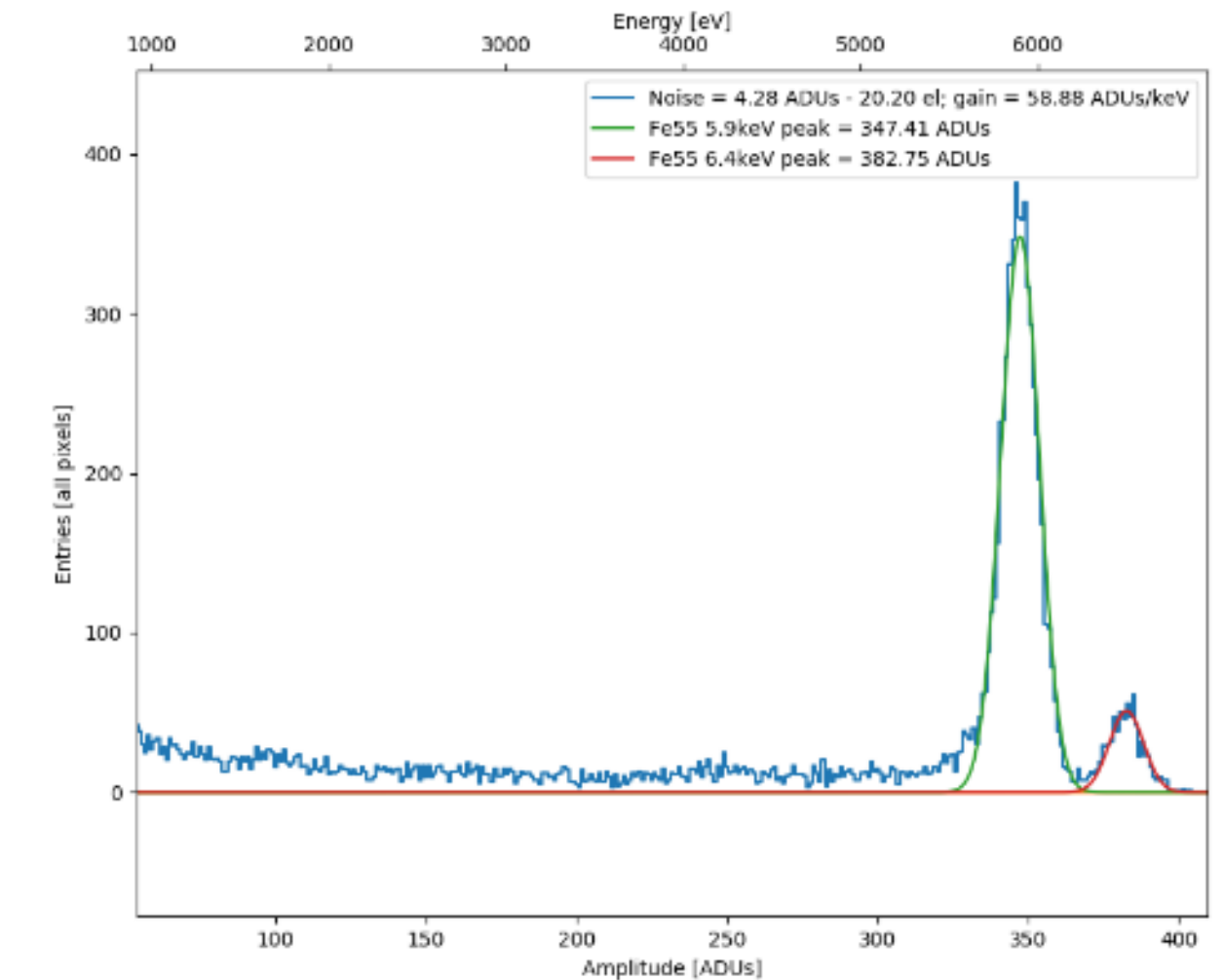


Collected charge at different x-widths and y-depths obtained with an Edge-TCT setup with a neutron fluence  $\Phi=3 \times 10^{14}$  neq/cm<sup>2</sup>.

## ePixM (LF 150nm): soft X-ray detector for LCLS-II



ePixM readout board



Fe55 spectrum measured with ePixM

- [1] W. Snoeys, J.D. Plummer, S. Parker and C. Kenney, *Pin detector arrays and integrated readout circuitry on high-resistivity float-zone silicon*, IEEE Trans. Electron Devices 41 (1994) 903.
- [2] J. D. Segal et al., *Second generation monolithic full-depletion radiation sensor with integrated CMOS circuitry*, in proceedings of IEEE NSS-MIC, Knoxville, U.S.A., 30 October–6 November 2010, pp. 1896–1900
- [3] L. Rota et al., *Design of ePixM, a fully-depleted monolithic CMOS active pixel sensor for soft X-ray experiments at LCLS-II*, Journal of Instrumentation, Volume 14, December 2019
- [4] C. Tamma et al., *The CHES-2 prototype in AMS 0.35 μm process: A high voltage CMOS monolithic sensor for ATLAS upgrade*, doi: 10.1109/NSSMIC.2016.8069856

# Large area MAPS – Highlights & Next Steps

## Approach:

- Engaged with the scientific community to share know-how
- Focus on long-term R&D, targeting simultaneously:
  - ~ns timing resolution
  - Power consumption compatible with large area and low material budget
  - Fault-tolerant circuit strategies for wafer-scale MAPS

## Highlights:

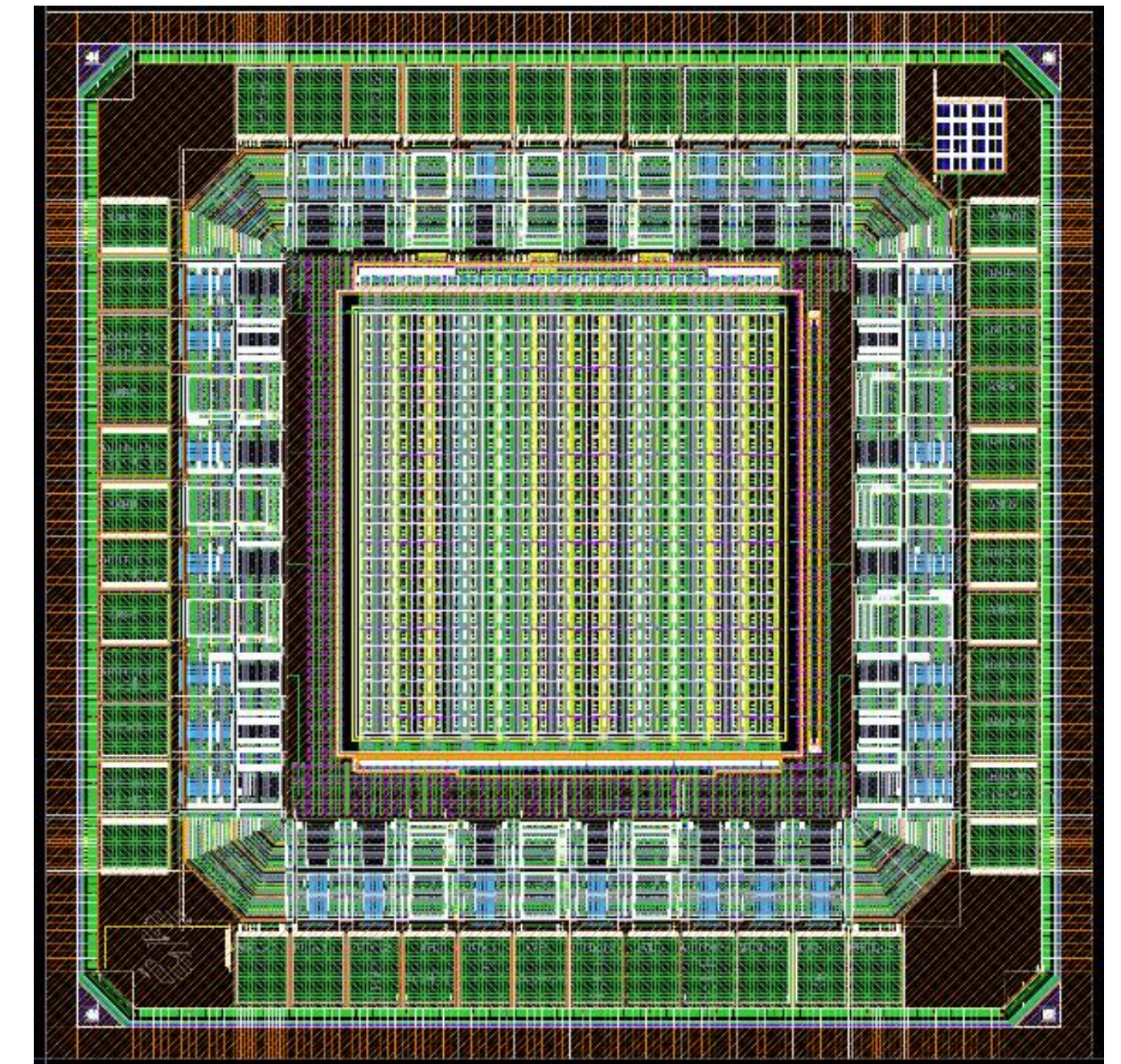
- Designed pixel architecture with binary readout optimized for linear colliders
- Submitted a small pixel matrix for fabrication on CERN WP1.2 shared run
- Architecture will allow us to evaluate technology in terms of defects and RTS

## Next steps:

- Evaluate performance of 1st SLAC prototype on TJ65nm (2023).
- New design combining O(ns) timing precision and low-power (2024/2025).
- **Stretch Goals:** design of a wafer-scale ASIC (2025/2026, design only)

## Engagement :

- Higgs Factory detector initiative R&D
- DRD 7.6 on common issues of power distributions compatible with stitching

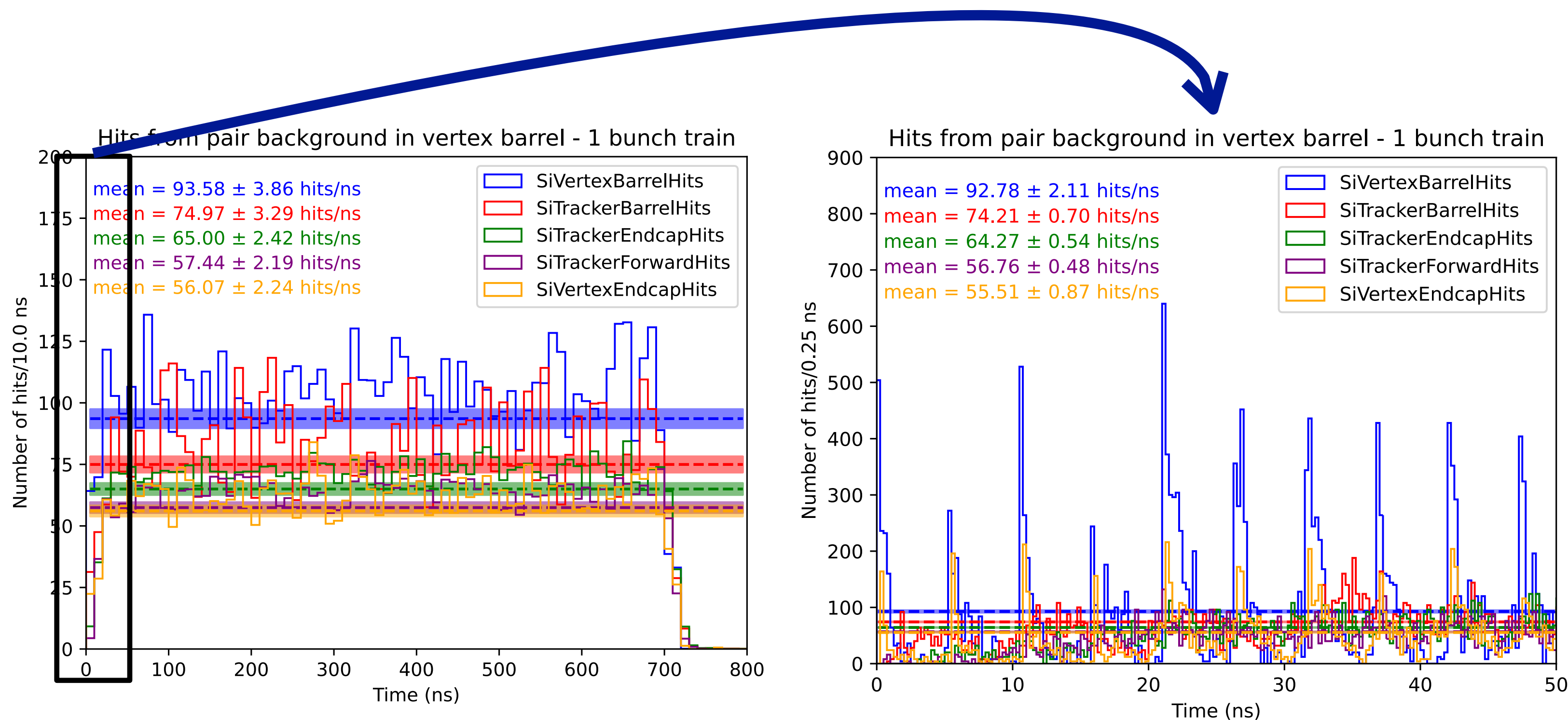


**Layout of SLAC prototype for WP1.2 2022 shared submission on TowerSemi 65nm**

# Tracking performance

O(ns) timing capabilities as an additional handle to suppress beam induced backgrounds

Time distribution of hits per unit time and area:  $\sim 4.4 \cdot 10^{-3}$  hits/(ns · mm<sup>2</sup>)  $\approx 0.03$  hits/mm<sup>2</sup> /BX  
in the 1st layer of the vertex barrel SiD-like detector for ILC/C<sup>3</sup>

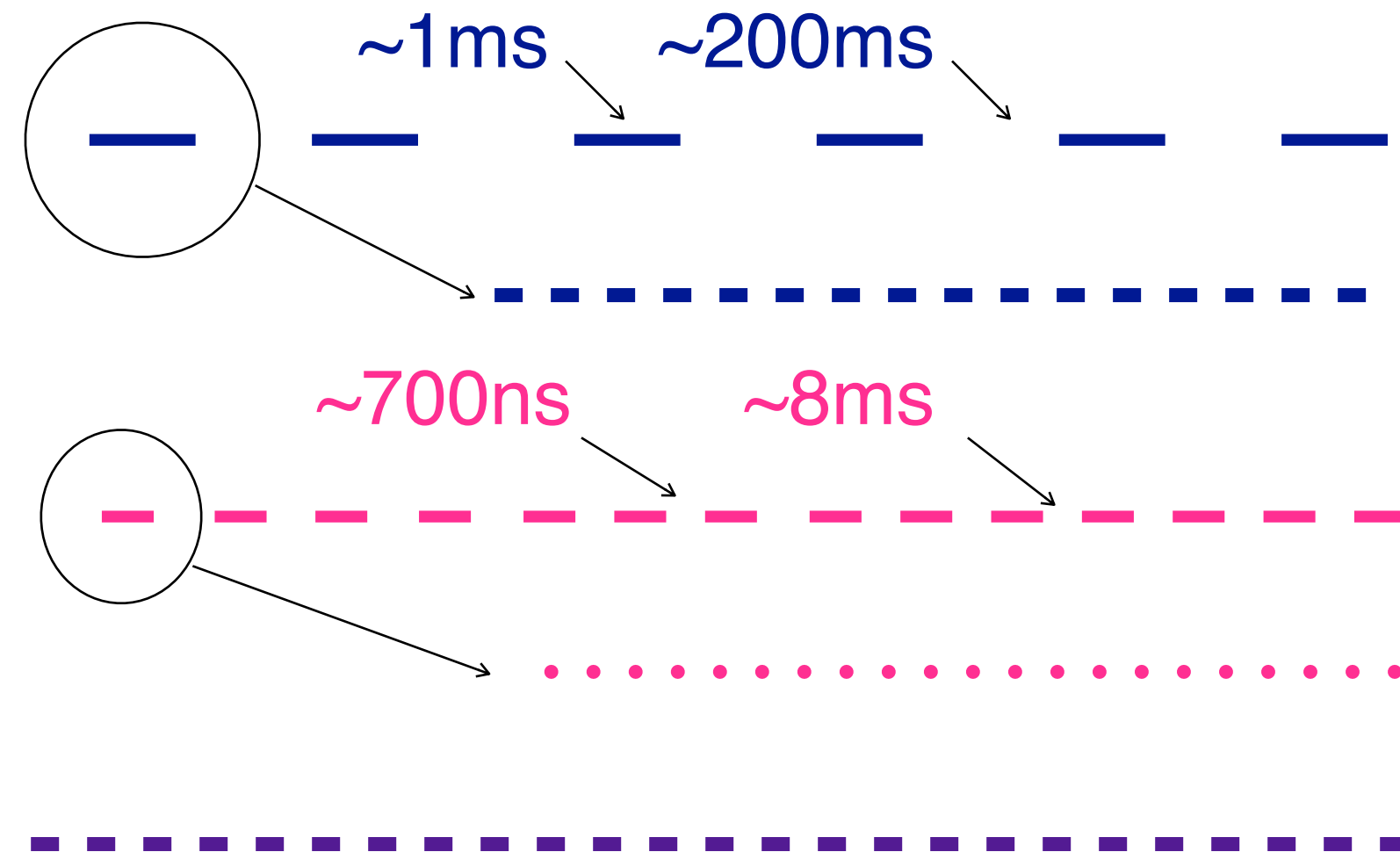


Parameter	Value
Time resolution	1 ns-rms
Spatial Resolution	7 μm
Expected charge from a MIP	500 – 800 e/h
Minimum Threshold	200 e-
Noise	< 30 e-rms
Power density	< 20 mW/cm <sup>2</sup>
Maximum particle rate	1000 hits/cm <sup>2</sup>

**D. Ntounis talk on beam background simulations at ECFA 2023**



# Beam Format and Detector Design Requirements



**ILC** Trains at 5Hz, 1 train 1312 bunches  
Bunches are 369 ns apart

**C<sup>3</sup>** Trains at 120Hz, 1 train 133 bunches  
Bunches are 5 ns apart

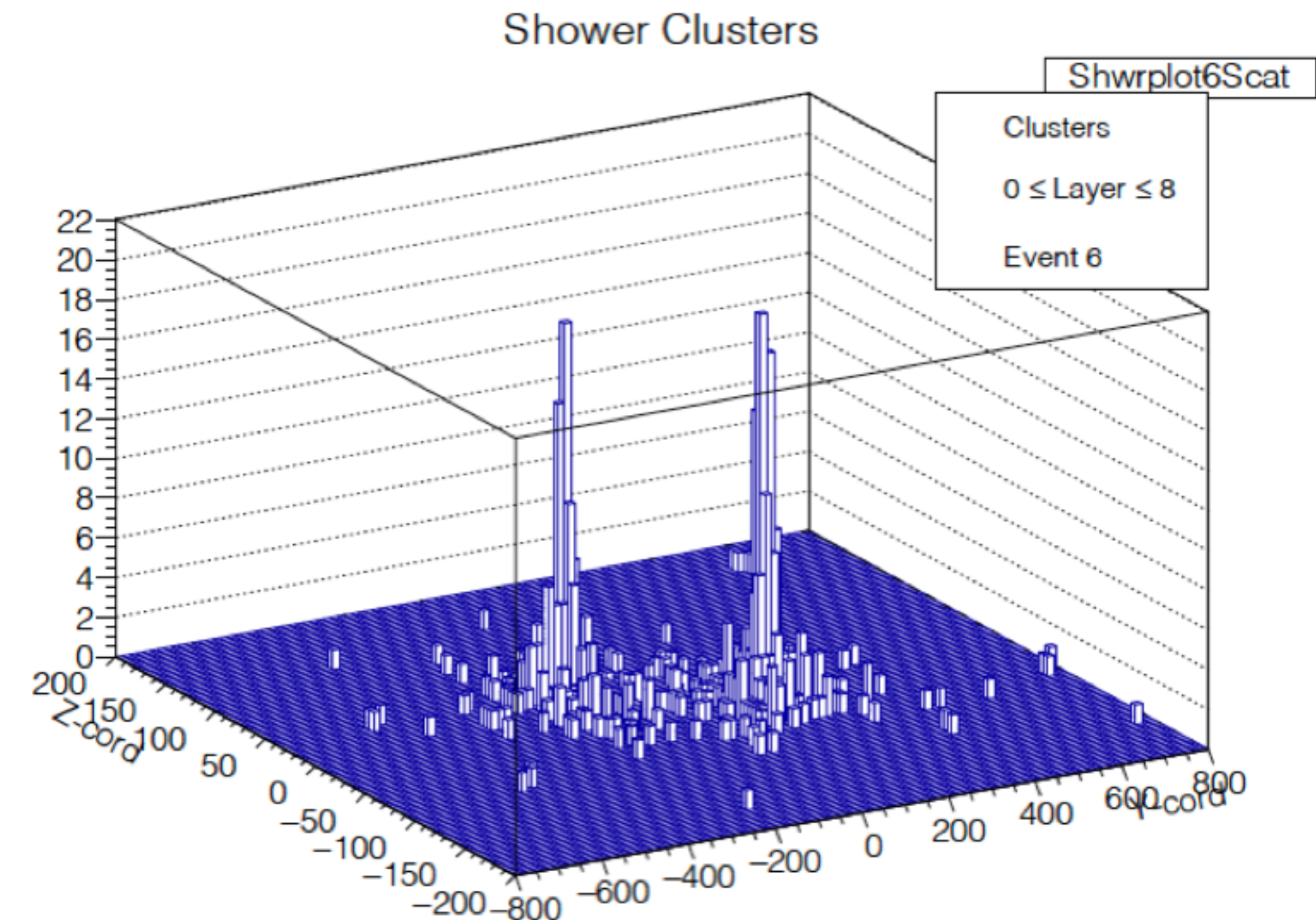
**FCC@ZH** Bunches 1  $\mu$ s apart  
**FCC@Z** Bunches 20 ns apart

- Very low duty cycle at LC (0.5% ILC, 0.03% C<sup>3</sup>) allows for trigger-less readout and power pulsing
  - Factor of 100 power saving for front-end analog power
  - **O(1-100) ns bunch identification capabilities**
- Impact of beam-induced background to be mitigated through MDI and detector design
  - Timing resolution of O(ns) can further suppress beam-backgrounds and keep occupancy low
  - **O(1-10) ns for beam background rejection and/or trigger decision before reading out the detector**
  - Tracking detectors need to achieve good resolution while mitigating power consumption

# MAPS for ECal

Fine granularity allows for identification of two showers down to the mm scale of separation

- SiD detector configuration with  $25 \times 100 \mu\text{m}^2$  pixel in the calorimeter at ILC
- With no degradation of the energy resolution
- ***The design of the digital MAPS applied to the ECal exceeds the physics performance as specified in the ILC TDR***
- The 5T magnetic field degrades the resolution by a few per cent due to the impact on the lower energy electrons and positrons in a shower
- Future planned studies include the reconstruction of showers and  $\pi^0$  within jets, and their impact on jet energy resolution



**GEANT4 simulations of Transverse distribution of two 10 GeV showers separated by one cm**

# Target Specs vs. State of the Art

Chip name	Technology	Pixel pitch [ $\mu\text{m}$ ]	Pixel shape	Time resolution [ns]	Power Density [mW/cm <sup>2</sup> ]
<b>Target Specification</b>	<b>?</b>	<b>25 x 100</b>	<b>Sq / rect</b>	<b>1</b>	<b>&lt; 20</b>
ALPIDE [2][3]	Tower 180 nm	28	Square	< 2000	5
FastPix [4][5]	Tower 180 nm	10 - 20	Hexagonal	0.122 – 0.135	>1500
DPTS[6]	Tower 65 nm	15	Square	6.3	53
Cactus [7]	LF 150 nm	1000	Square	0.1-0.5	145
MiniCactus [8]	LF 150 nm	1000	Square	0.088	300
Monolith [9][10]	IHP SiGe 130 nm	100	Hexagonal	0.077 – 0.02	40 - 2700

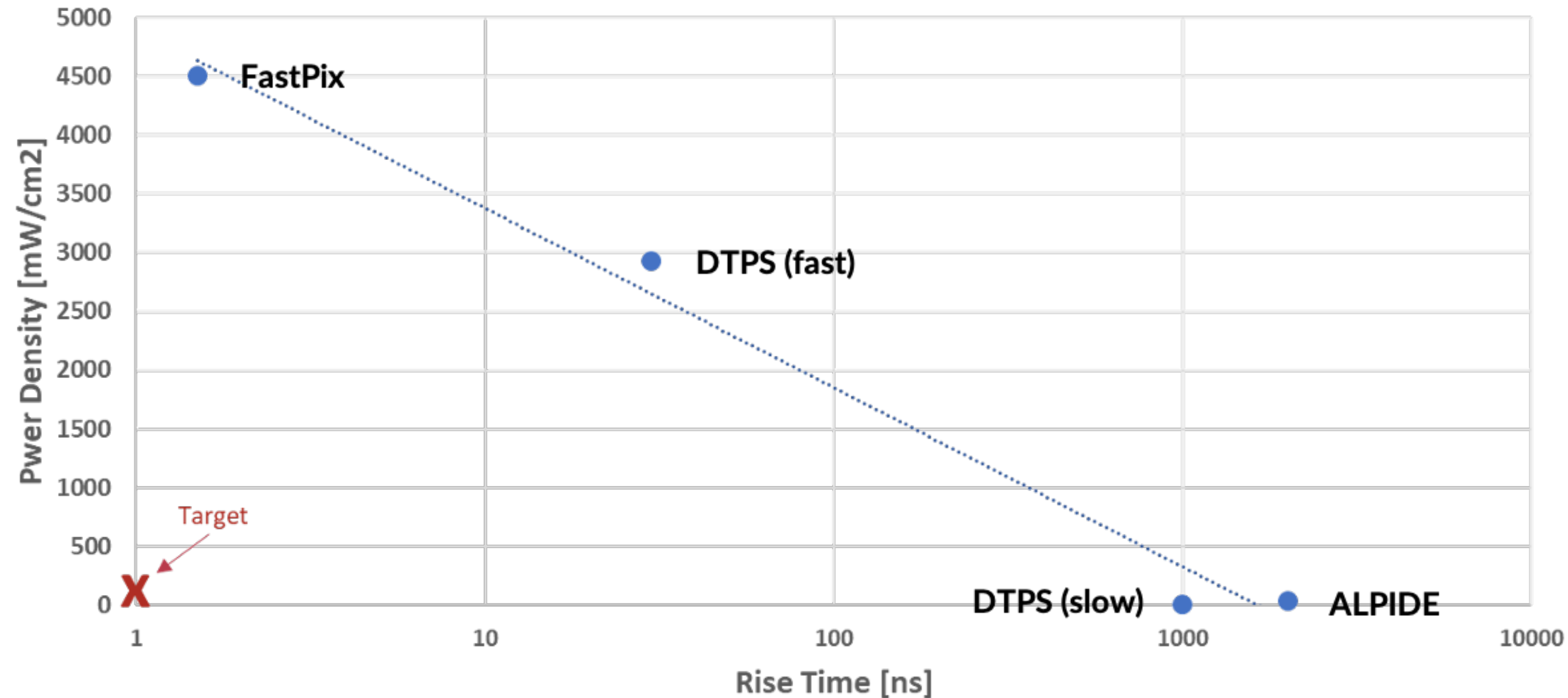


No design fulfills all target specification → The need to develop a custom design

We decided to go with the Tower 65nm technology, which has been optimized by CERN WP1.2 to have low sensor capacitance allowing very good performance with low power consumption.

- + it has the possibility of a wafer-scale stitched sensor
- + it has been proven to be radiation tolerant

# Target Specs vs. State of the Art



No design fulfills all target specification → The need to develop a custom design

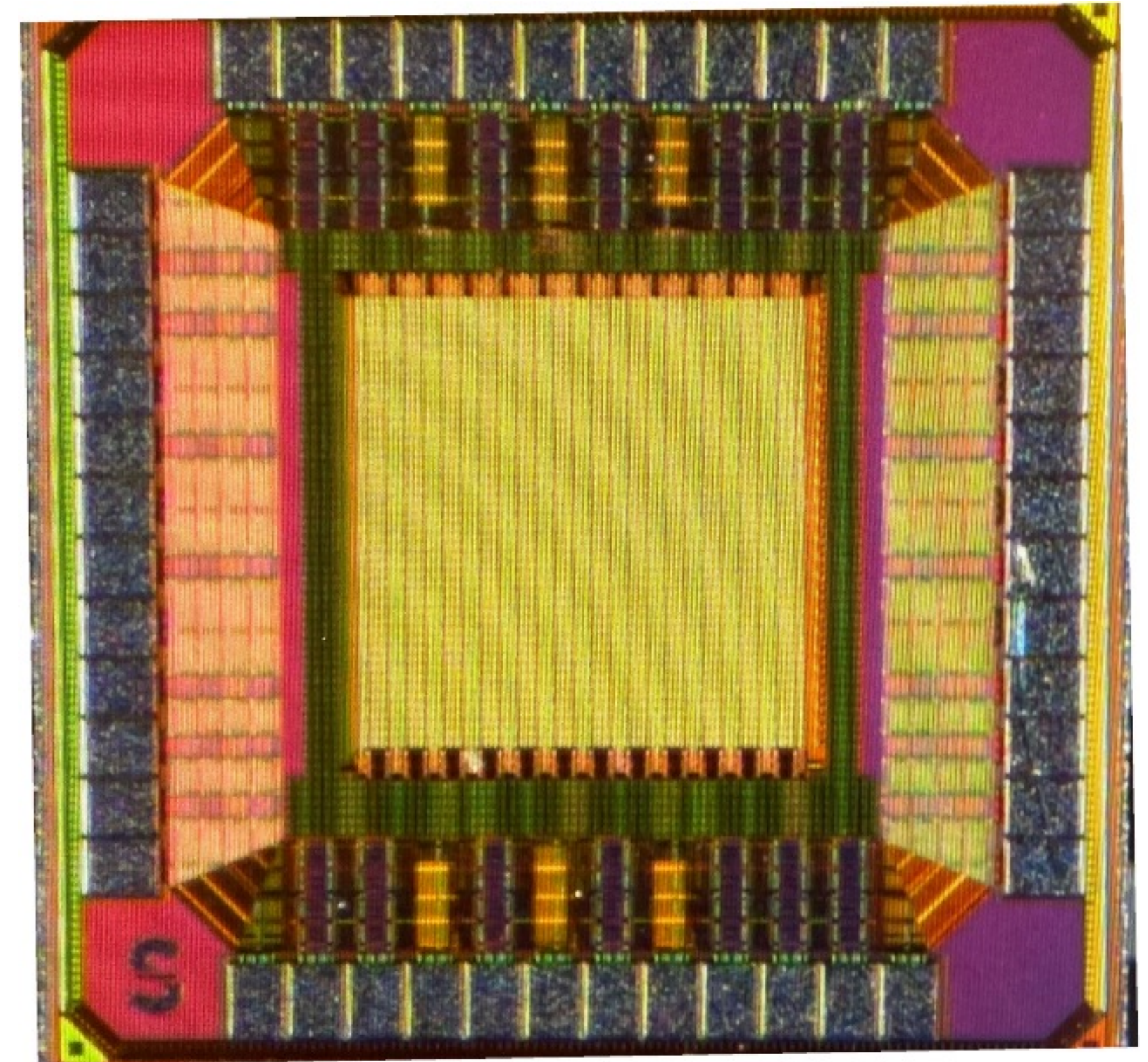
We decided to go with the Tower 65nm technology, which has been optimized by CERN WP1.2 to have low sensor capacitance allowing very good performance with low power consumption.

- + it has the possibility of a wafer-scale stitched sensor
- + it has been proven to be radiation tolerant

# NAPA\_p1: NAnosecond Pixel for large Area sensors – Prototype 1

## First prototype in TJ 65nm

- The prototype design submitted with a total area 5 mm x 5 mm and a pixel of  $25\ \mu\text{m} \times 25\ \mu\text{m}$ , to serve as a baseline for sensor and pixel performance.
- Design motivation → simple architecture with minimum global signals to reduce failure risk in a large area implementation.
- Thanks to CERN WP1.2 effort on sensor optimization in TowerSemi 180 nm and 65 nm technologies

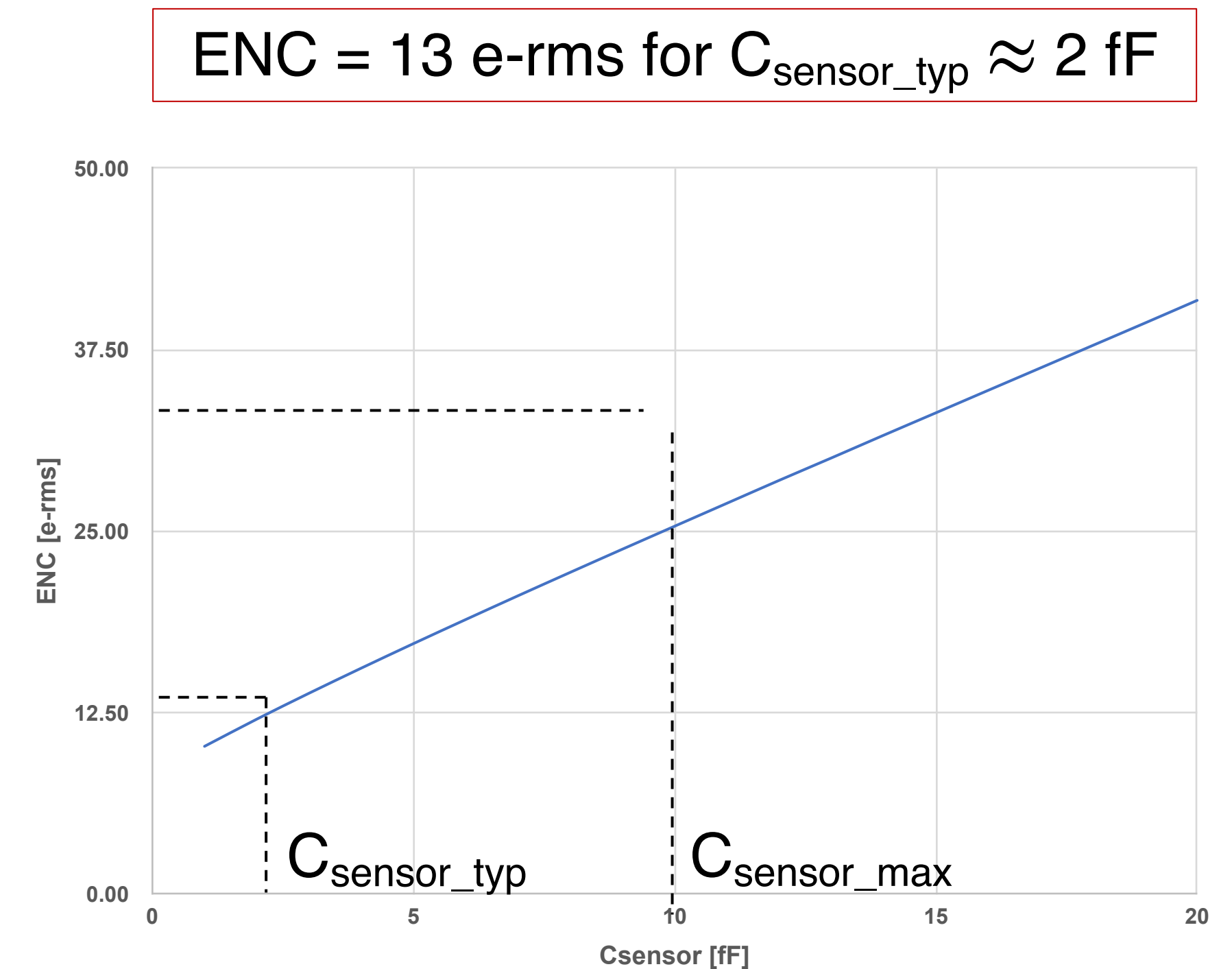


*Picture of NAPA-p1 prototype from WP1.2 shared submission*

**JINST 19 (2024) 04, C04033**

# Summary of NAPA-p1 Performance

	Specification	Simulated NAPA-p1
<b>Time resolution</b>	1 ns-rms	0.4 ns-rms ✓
<b>Spatial Resolution</b>	7 $\mu\text{m}$	7 $\mu\text{m}$ ✓
<b>Noise</b>	< 30 e-rms	13 e-rms ✓
<b>Minimum Threshold</b>	200 e-	~ 80 e- ✓
<b>Average Power density</b>	< 20 mW/cm <sup>2</sup>	0.1 mW/cm <sup>2</sup> for 1% duty cycle ✓

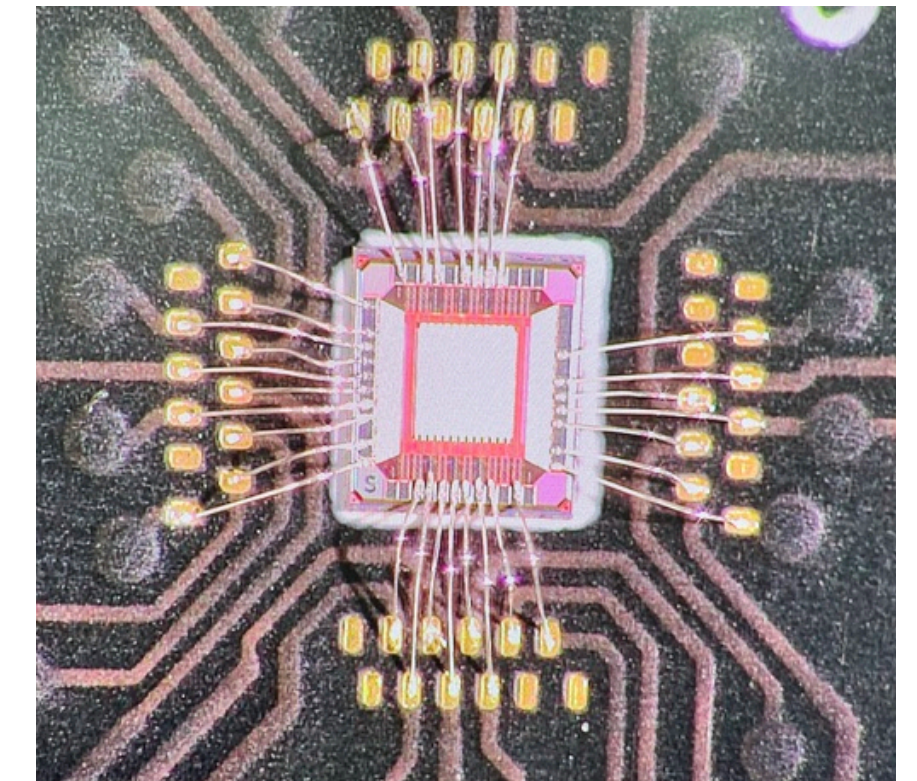


Acknowledgement: to CERN WP 1.2 for the excellent cooperation: NAPA-p1 uses the pixel masked developed and optimized by CERN, and was fabricated in a MLR led by CERN

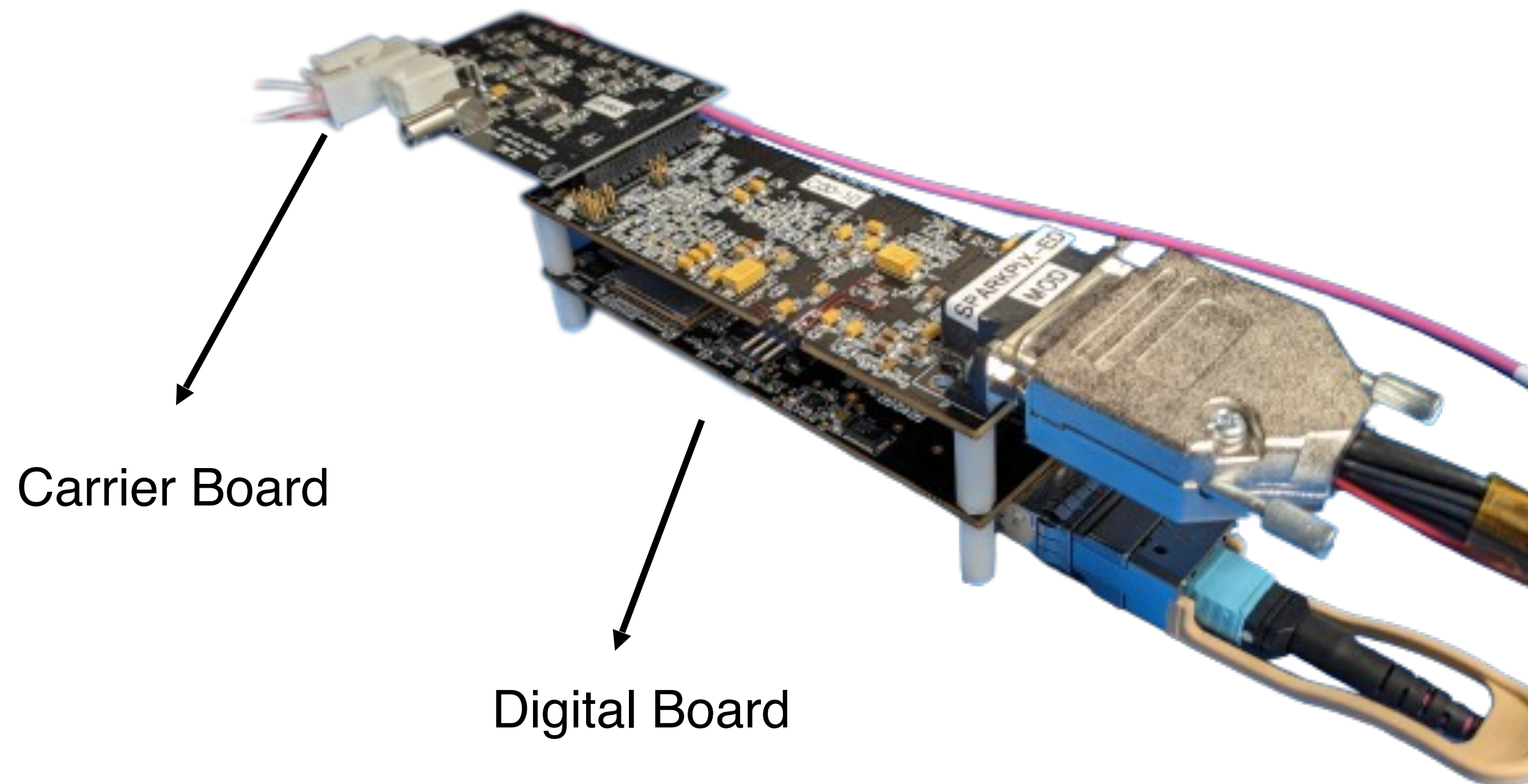
# Test Setup for NAPA-p1

Chips were received in September 2023

- A custom carrier was designed at SLAC for the NAPA-p1 chip providing all analog references
- The chip was wire-bonded at SLAC
- The carrier boards connects to a digital board containing an FPGA and several DAC's

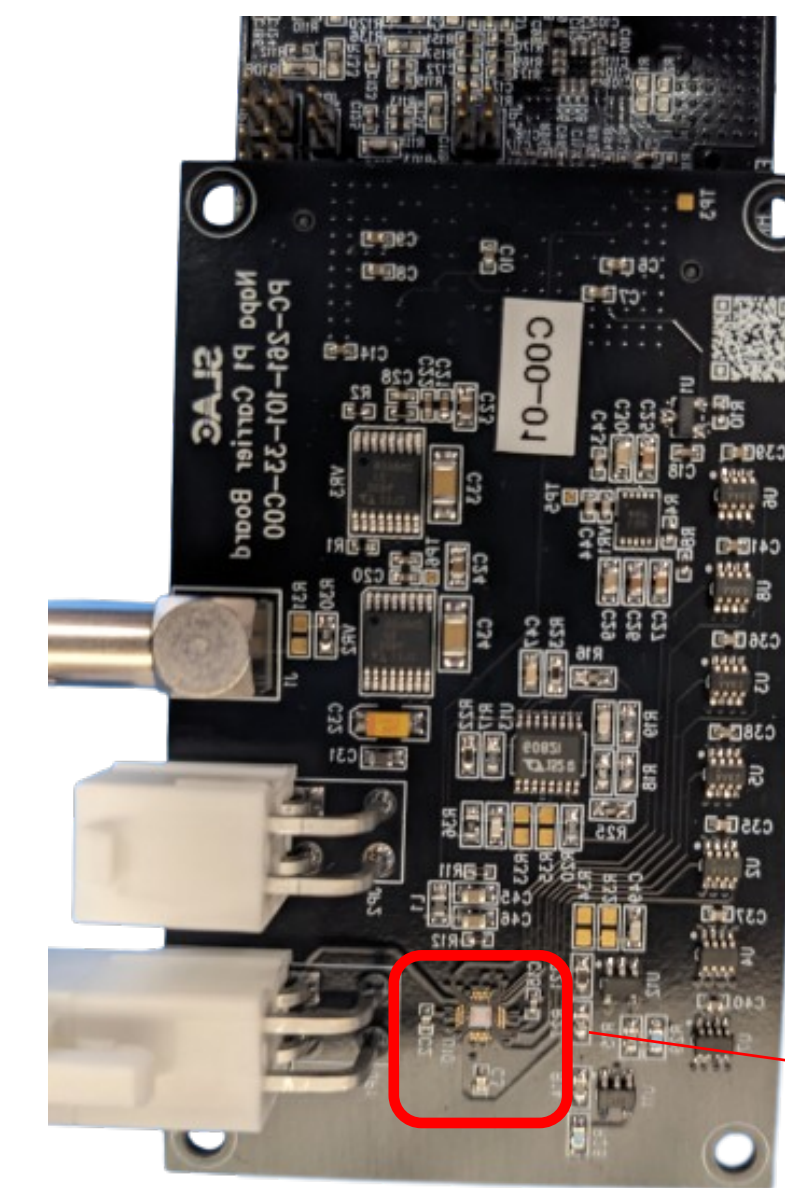


*Napa-p1*



Carrier Board

Digital Board

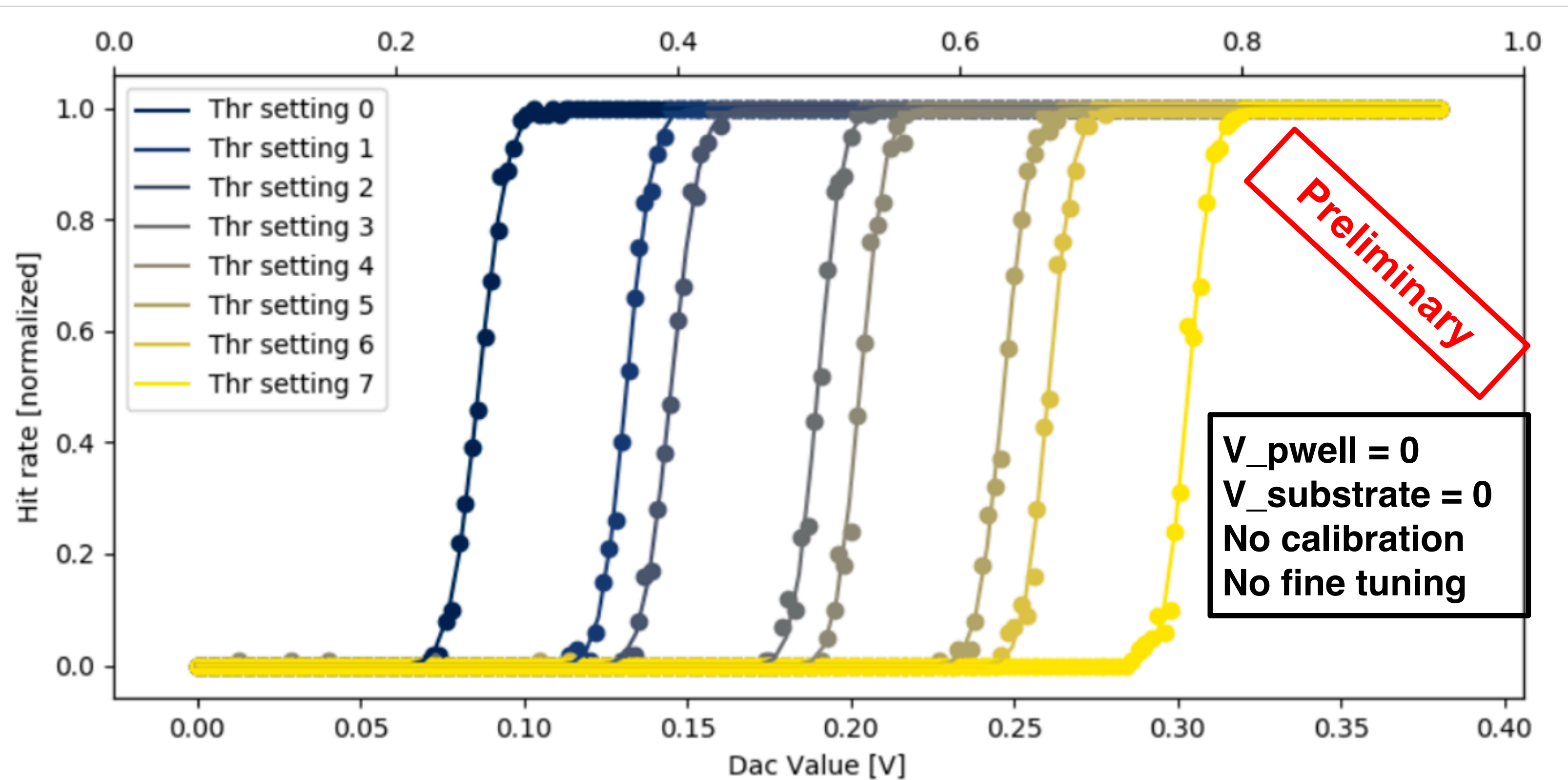
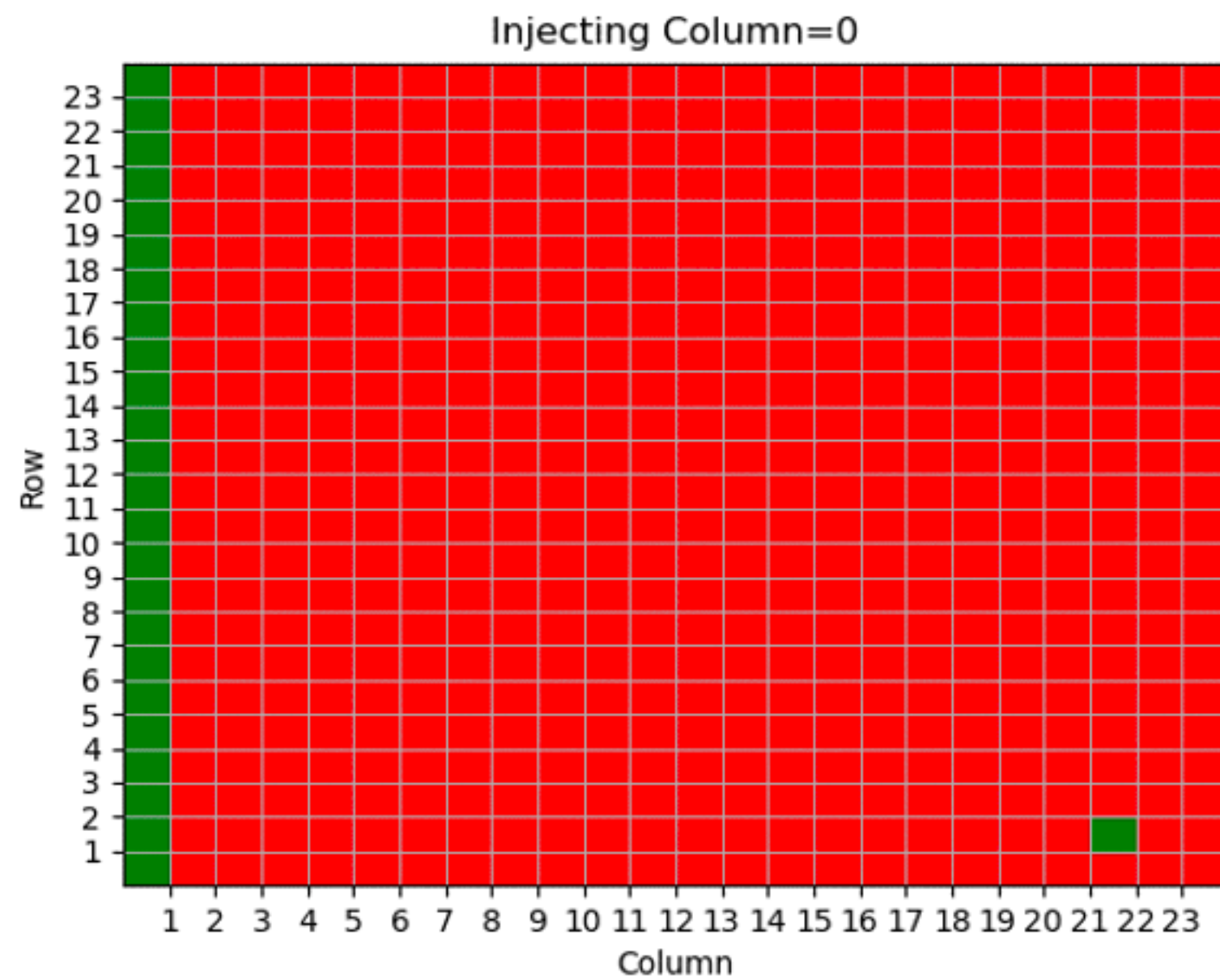


NAPA\_p1

Carrie Board

# Preliminary Characterization Results

Chip characterization is on going



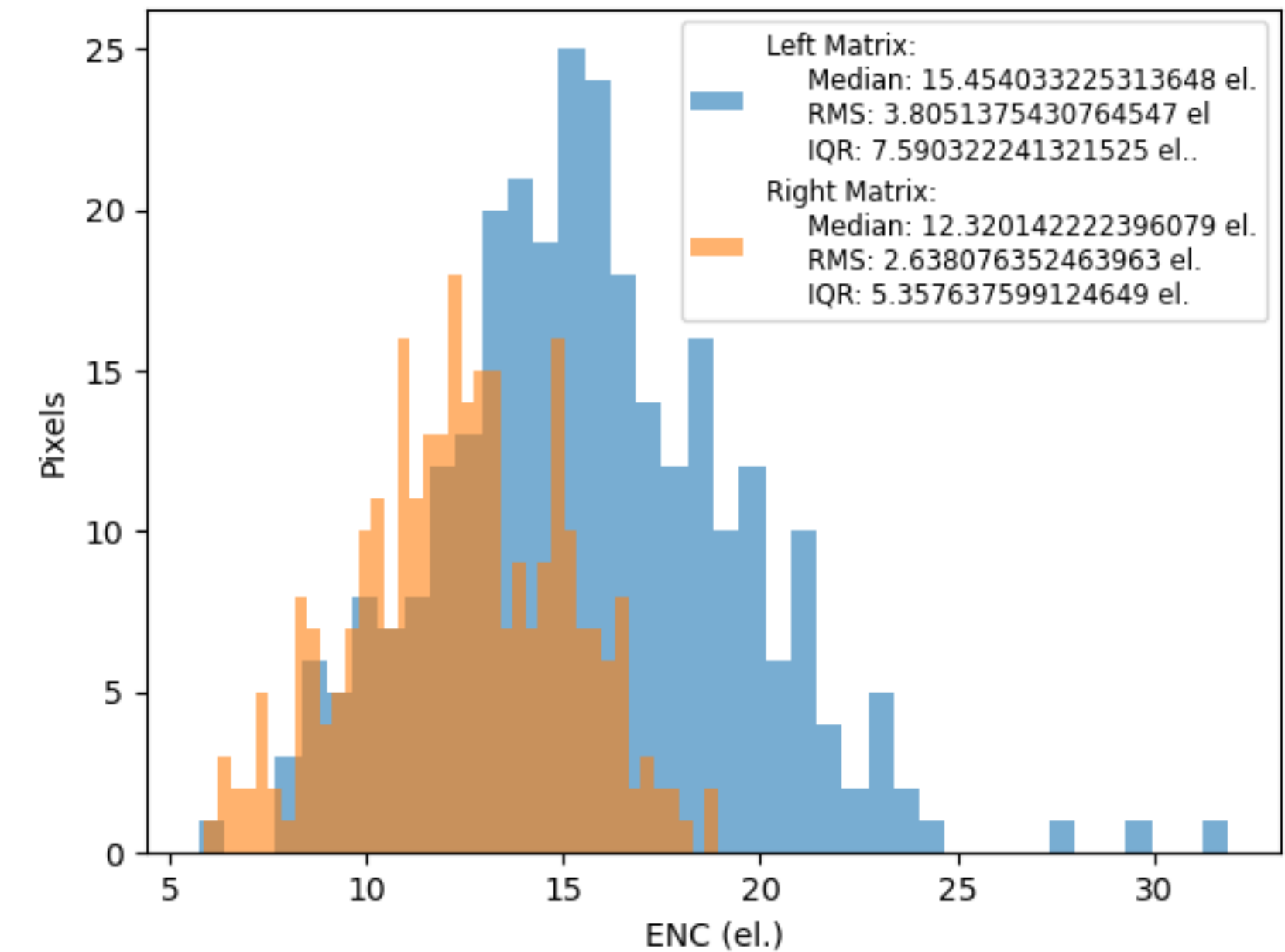
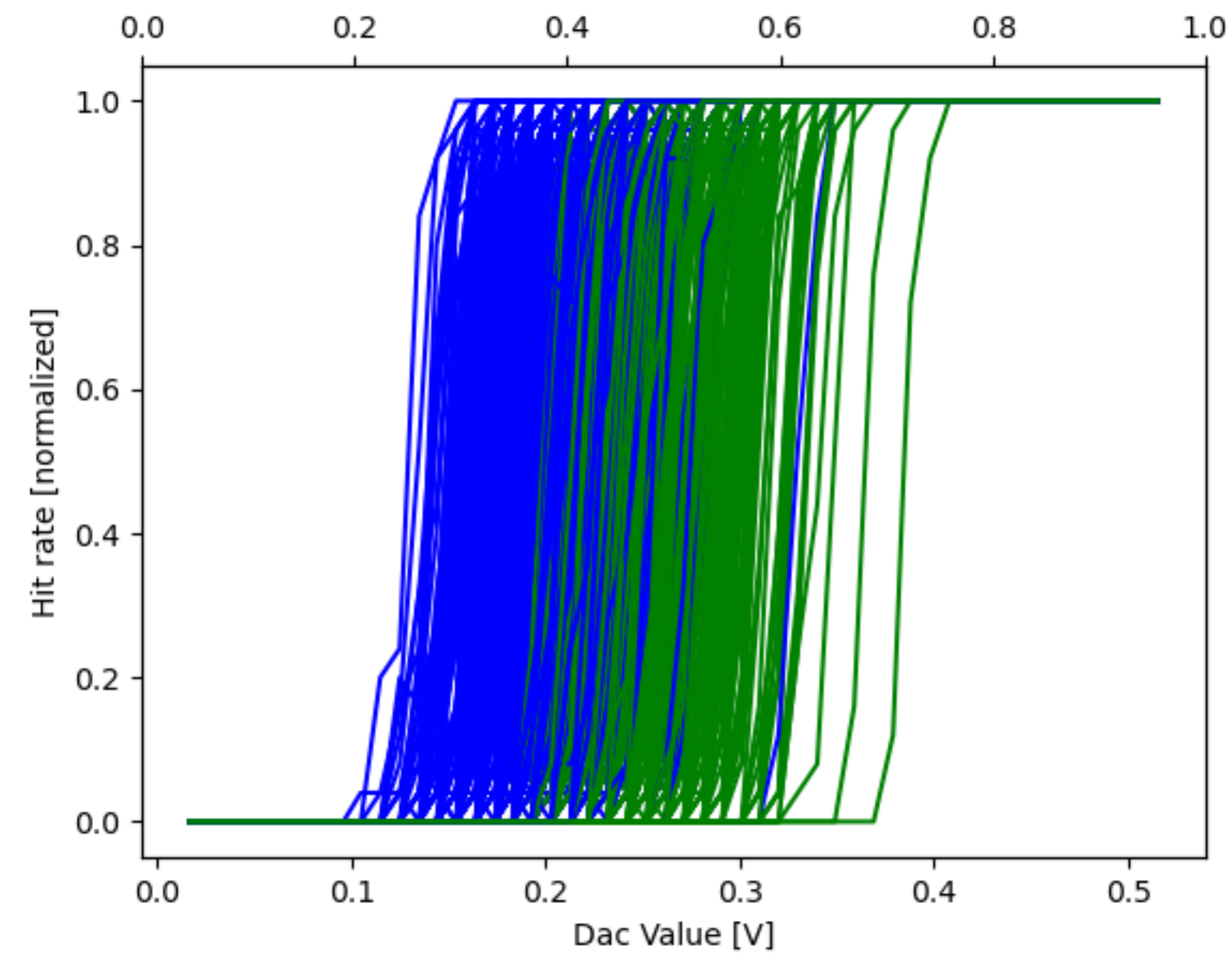
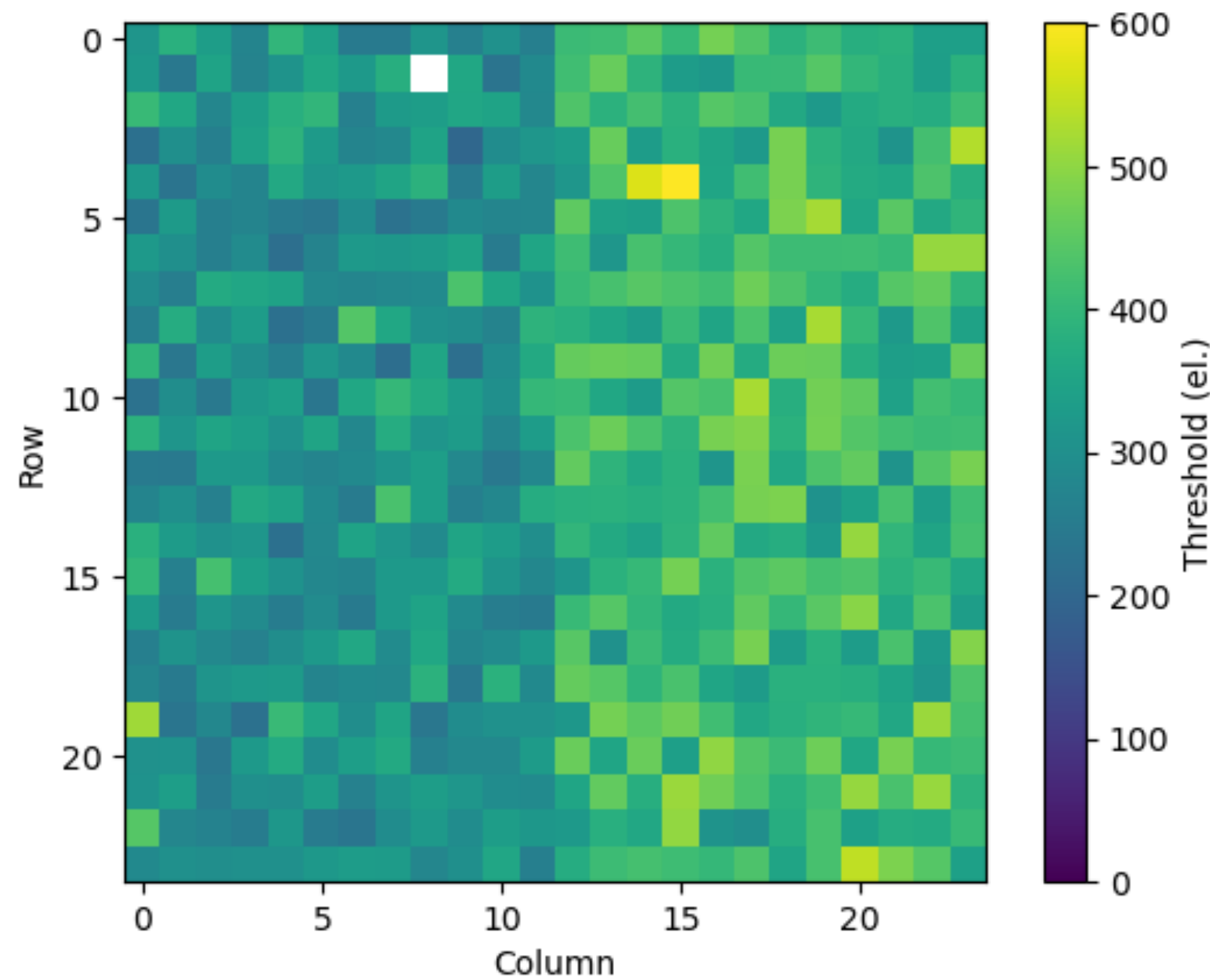


# Preliminary Characterization Results

Chip characterization is on going: Preliminary results match simulation

**Left Matrix:**  
Nominal Pixel  
Variant

**Right Matrix:**  
Pixel Variant with  
DC leakage current  
compensation



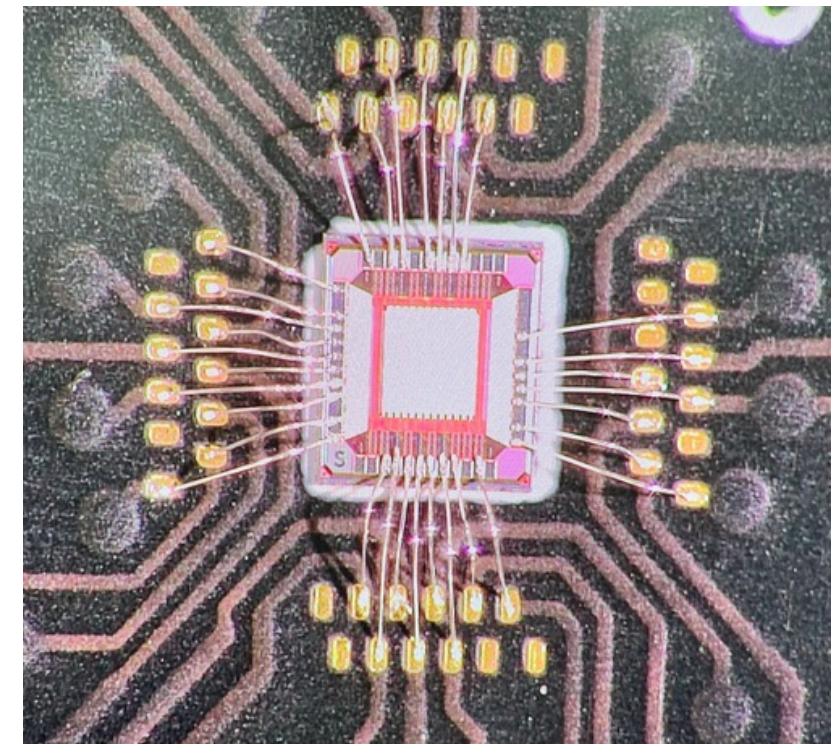
DC leakage current  
variant has less noise

# Conclusions and next steps

First MAPS prototype within CERN WP1.2 collaboration targeting  $e^+e^-$  requirements is being tested

- MAPS technology is being investigated for applications at future  $e^+e^-$  colliders for both tracking and calorimetry applications
- Developed first prototype within CERN WP1.2 based on T<sub>J</sub> 65nm processing
  - Simulations of NAPA-p1 show that it is possible to achieve a time resolution 1 ns-rms with reasonably low power consumption of  $\sim 100 \text{ mW/cm}^2 \times \text{Duty Cycle}$
  - First characterization of Napa-p1 is promising - more ongoing
  - Design of NAPA-p2 has started to tackle large sensor challenges
    - NAPA-p2 will serve as a system proof of concept
- Requirements derived for LC but many of the challenges of deploying this technology are common: power distribution, low yield ...
  - Technical problems which are independent of the application which require international collaboration to tackle
  - Engagement within the DRD7.6 collaboration to develop specific block to be included in the next engineering run.

NAPA-p1



*Thank you!*

# Enabling technical capabilities at SLAC

## Microwave Annealing & Device modeling and simulations



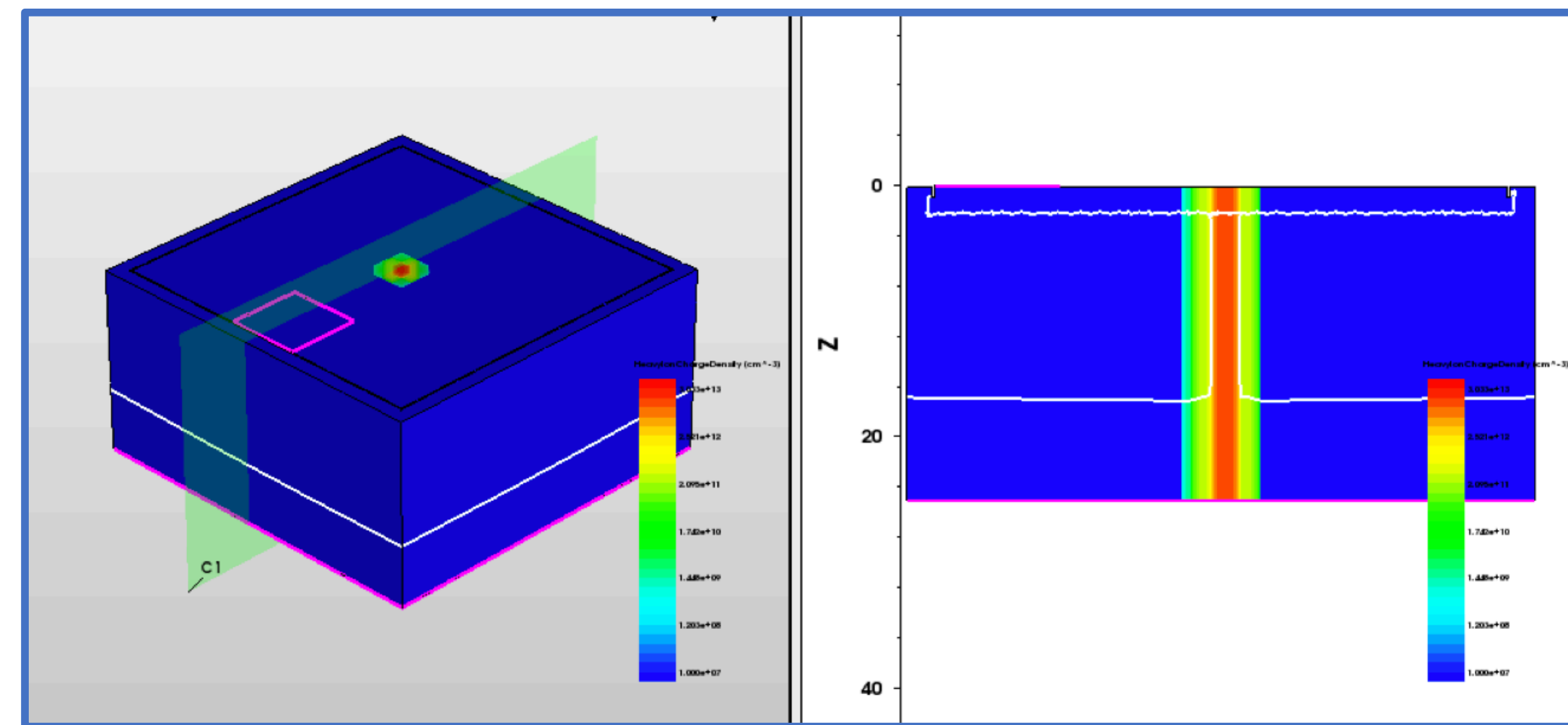
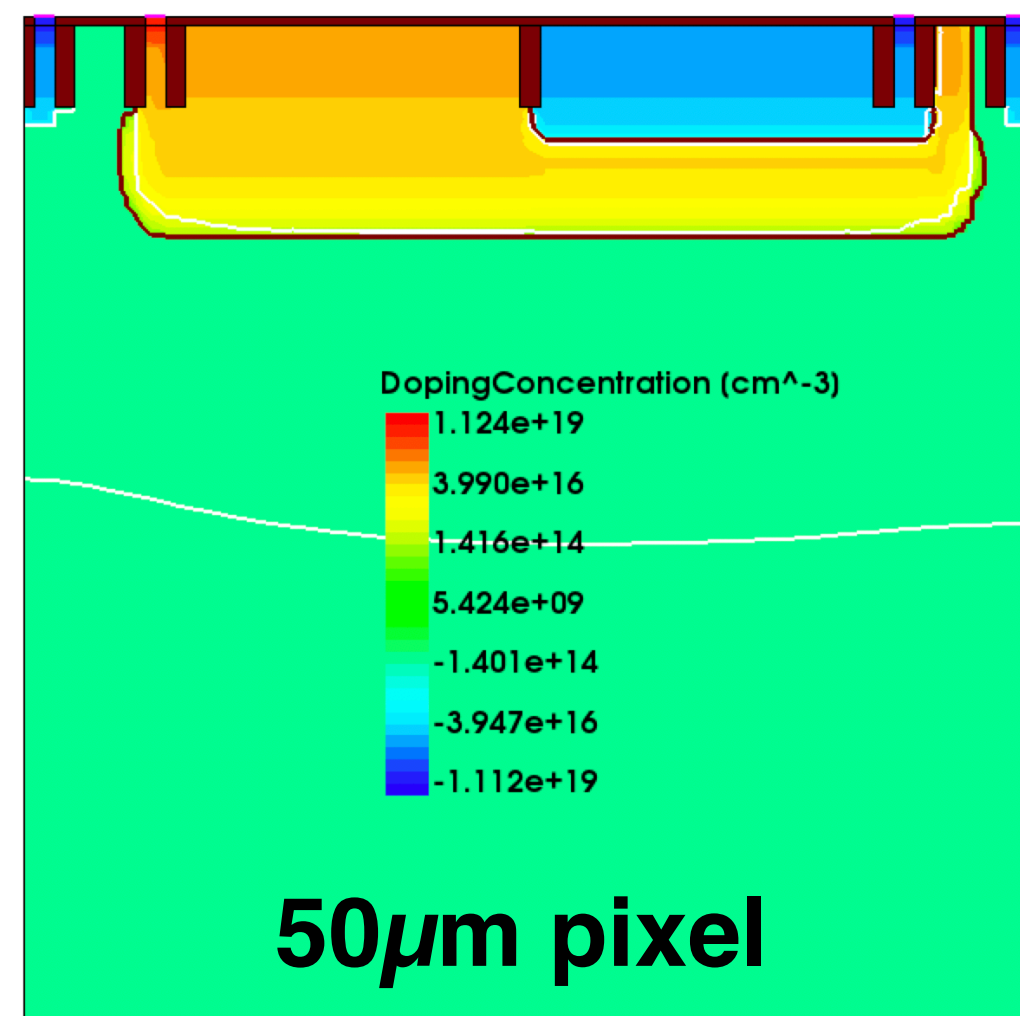
**AXOM Microwave Annealing System in SLAC cleanroom**

- Optimization of material to obtain desired properties (semiconductors, ceramics, polymers) often requires annealing (heat)
- Heat may change, damage or destroy other elements of a structure
- Heating materials is energy intensive process
- Microwave annealing (MWA) is a non-equilibrium annealing technique which selectively transfers energy to defects, dopants, interfaces or impurities
  - Tool facilitates development of novel device structures for sensors, ASICs
  - SLAC has developed several HEP applications using microwave annealing
  - MWA is compatible with CMOS processing, allowing advanced integration
- Experience in Device modeling and simulations
  - TCAD full characterization of new processes

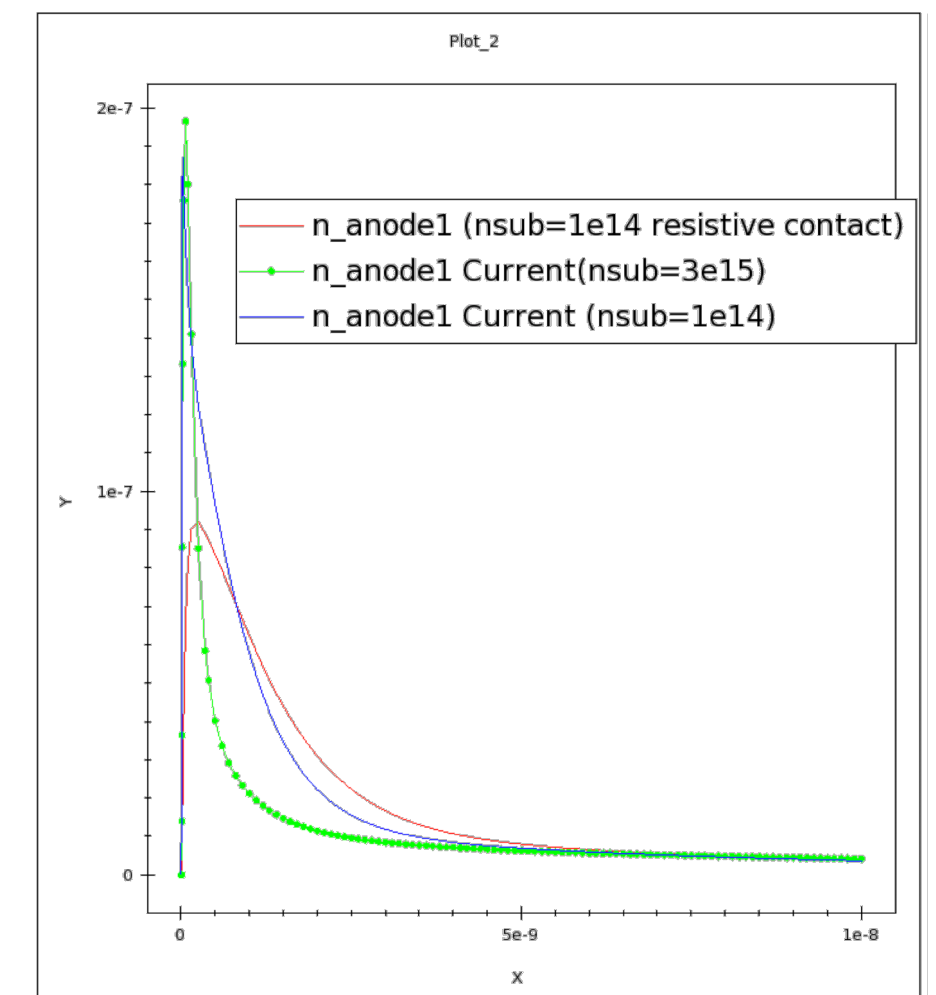
# MAPS on novel CMOS technologies

## Blue-sky R&D on CMOS 22nm FDSOI

- Fully-Depleted Silicon-On-Insulator process enables implementation of sensor in substrate
- Promising CMOS process with excellent mixed-signal performance
- TCAD simulations and initial pixel design to evaluate key performance parameters:
  - Detector capacitance
  - Charge collection time
  - Cross-talk



3D Charge collection simulations (MIP)

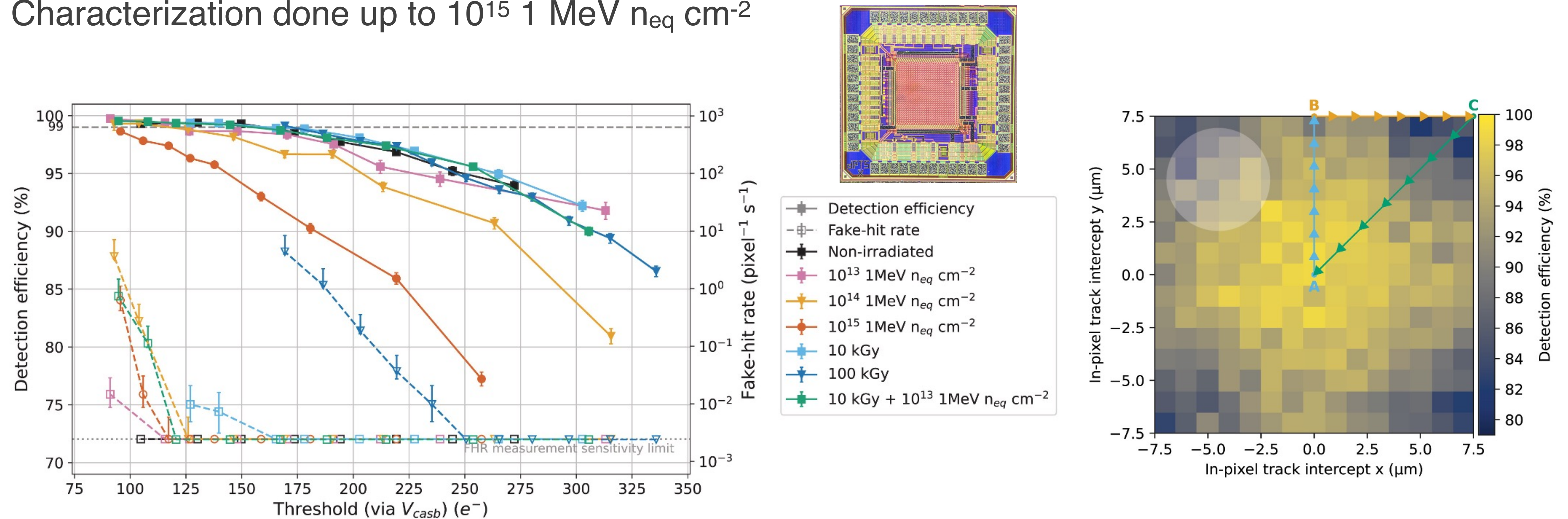


Read-out current:  
compare three process options

# Recent results with Digital Pixel Test Structures

Synergies with DPTS characterization at CERN test beam facility within ALICE Collaboration

Characterization done up to  $10^{15}$  1 MeV  $n_{eq}$   $cm^{-2}$



Digital pixel test structures implemented in a 65 nm CMOS process  
A Compact Front-End Circuit for a Monolithic Sensor in a 65-nm CMOS Imaging Technology

# Current status of beam-background studies

## Similar tools and methodology between ILC & FCC within Key4HEP

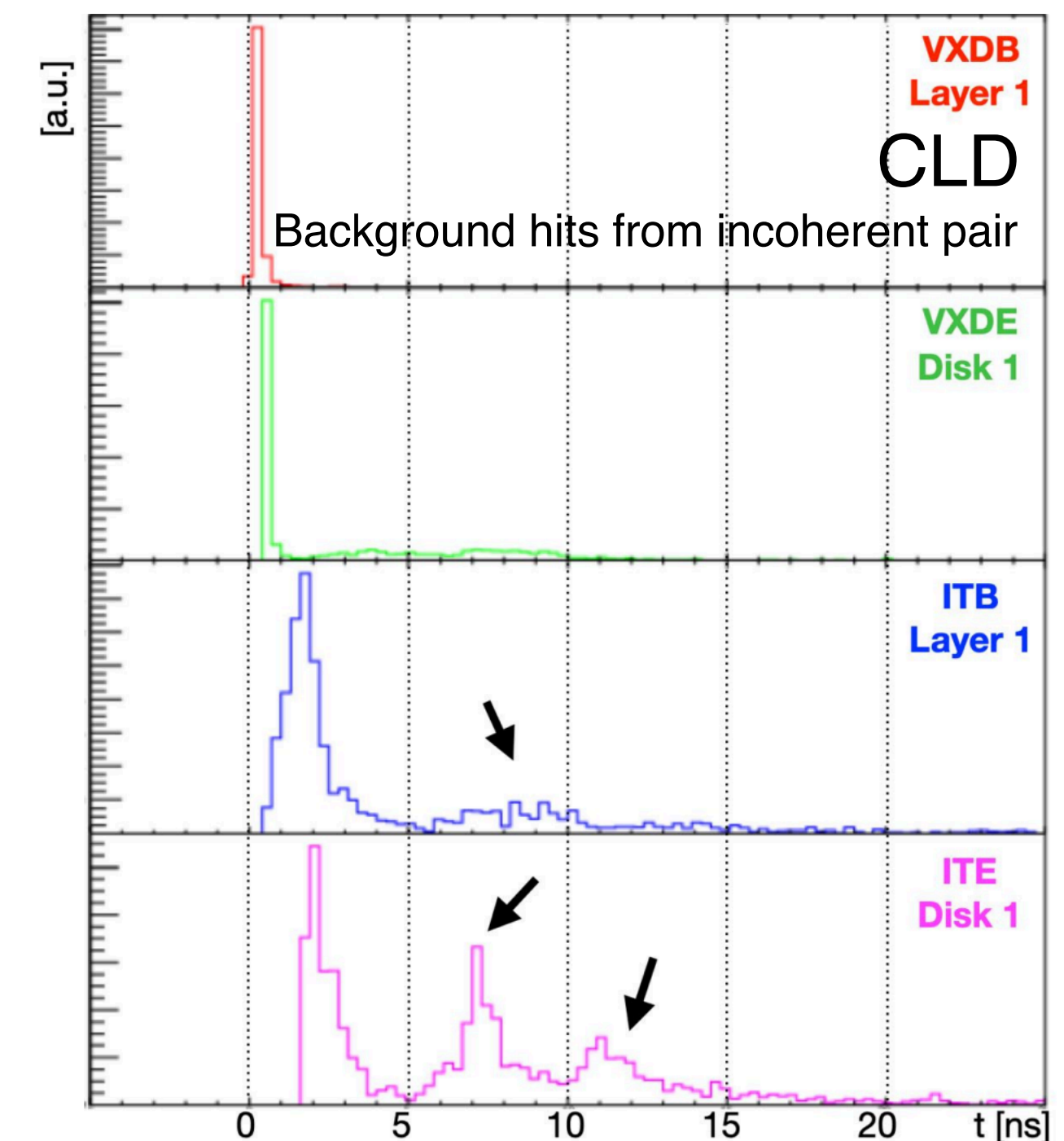
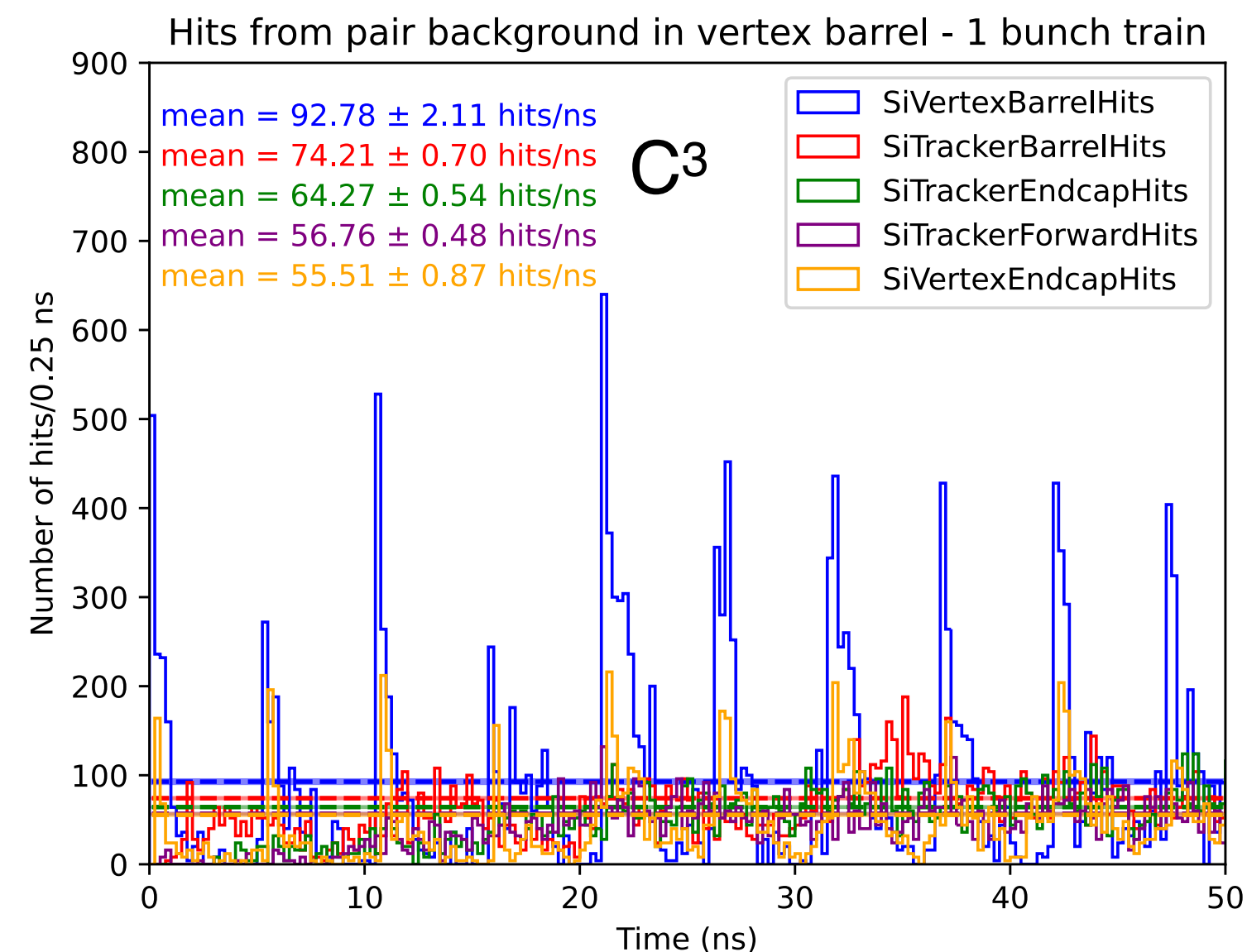
- ILC physics studies are based on full simulation data and some have been recently repeated for C<sup>3</sup>
  - Time distribution of hits per unit time and area on 1st layer  $\sim 4.4 \cdot 10^{-3} \text{ hits}/(\text{ns} \cdot \text{mm}^2) \approx 0.03 \text{ hits}/\text{mm}^2 / \text{BX}$
- CLD detailed studies @FCC show an overall occupancy of 2-3% in the vertex detector at the Z pole
  - assuming  $10\mu\text{s}$  integration time

$$\text{occupancy} = \text{hits}/\text{mm}^2/\text{BX} \cdot \text{size}_{\text{sensor}} \cdot \text{size}_{\text{cluster}} \cdot \text{safety}$$

$$\text{size}_{\text{sensor}} = \begin{matrix} 25\mu\text{m} \times 25\mu\text{m} \text{ (pixel)} \\ 1\text{mm} \times 0.05\text{mm} \text{ (strip)} \end{matrix} \quad \text{size}_{\text{cluster}} = \begin{matrix} 5 \text{ (pixel)} \\ 2.5 \text{ (strip)} \end{matrix} \quad \text{safety} = 3$$

	Z	WW	ZH	Top
<b>Bunch spacing [ns]</b>	30	345	1225	7598
<b>Max VXD occ. 1us</b>	2.33e-3	0.81e-3	0.047e-3	0.18e-3
<b>Max VXD occ. 10us</b>	23.3e-3	8.12e-3	3.34e-3	1.51e-3
<b>Max TRK occ. 1us</b>	3.66e-3	0.43e-3	0.12e-3	0.13e-3
<b>Max TRK occ. 10us</b>	36.6e-3	4.35e-3	1.88e-3	0.38e-3

Occupancy in readout window ( $10\mu\text{s}$ )



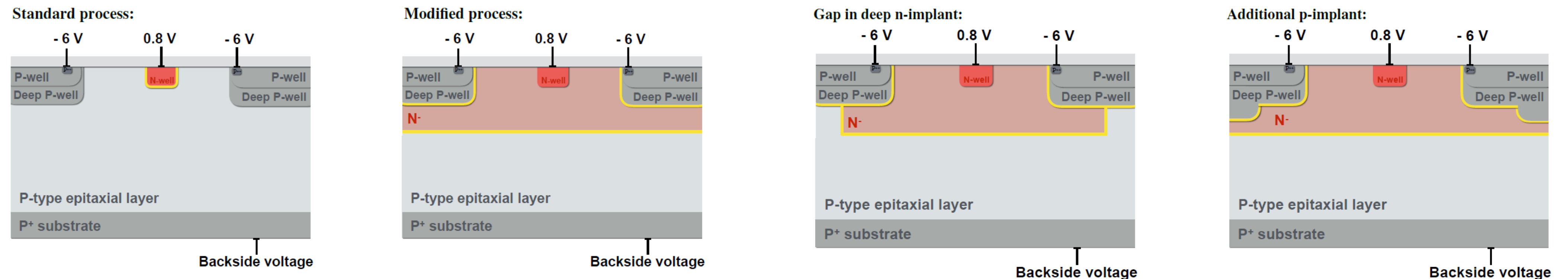
# Design Approach

For a constant SNR and  $Q_{in} \rightarrow$   $Power \propto (C_{sensor})^m$  with  $2 \leq m \leq 4$  as shown in [11]

**→ Aim for smallest possible sensor capacitance**

- Thanks to CERN WP1.2 effort on sensor optimization in TowerSemi 180 nm and 65 nm technologies [12] [13]
- **→  $C_{sensor}$  of 2-3 fF is achievable while maintaining high collection efficiency**

Jitter  $\propto \frac{C_{load}}{\sqrt{I}}$  with  $1 \leq n \leq 2$  **→ Keep  $C_{load}$  to a minimum and increase the current if needed.**



Sensor optimization in TowerSemi 180 nm process from [12] and [13]



# Going Towards a Large Sensor → Challenge

$$\Delta V = I_{pix} \times R_{Pix} + 2 \times I_{Pix} \times R_{Pix} + 3I_{Pix} \times R_{Pix} + \dots + N \times I_{Pix} \times R_{Pix}$$

$$\Delta V = I_{Pix} \times R_{Pix} (1 + 2 + 3 + \dots + N)$$

$$\Delta V = I_{Pix} \times R_{Pix} \times \frac{N(N+1)}{2}$$

Assuming :  $I_{pix} = 600 \text{ nA}$  and  $R_{pix} = 300 \text{ m}\Omega$

Assuming pixel of  $25 \mu\text{m} \times 25 \mu\text{m}$

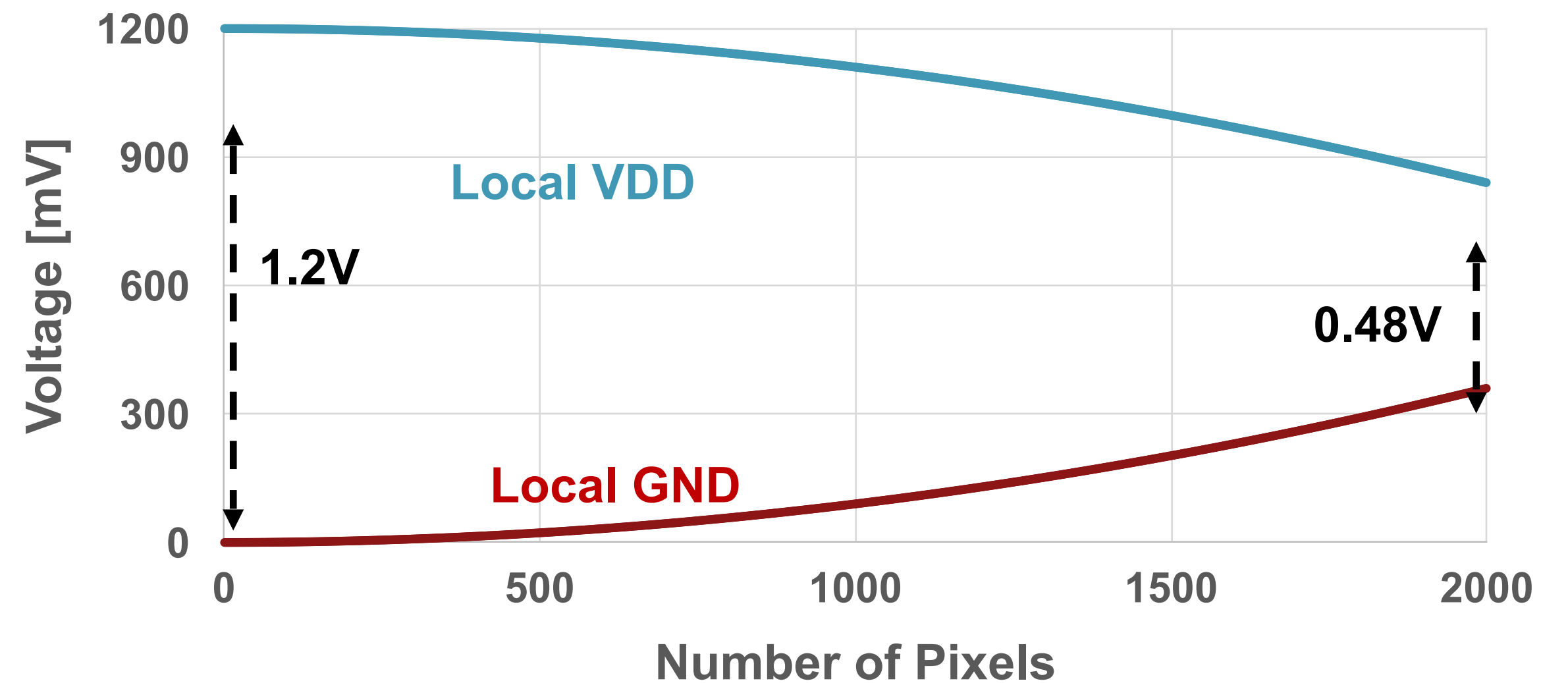
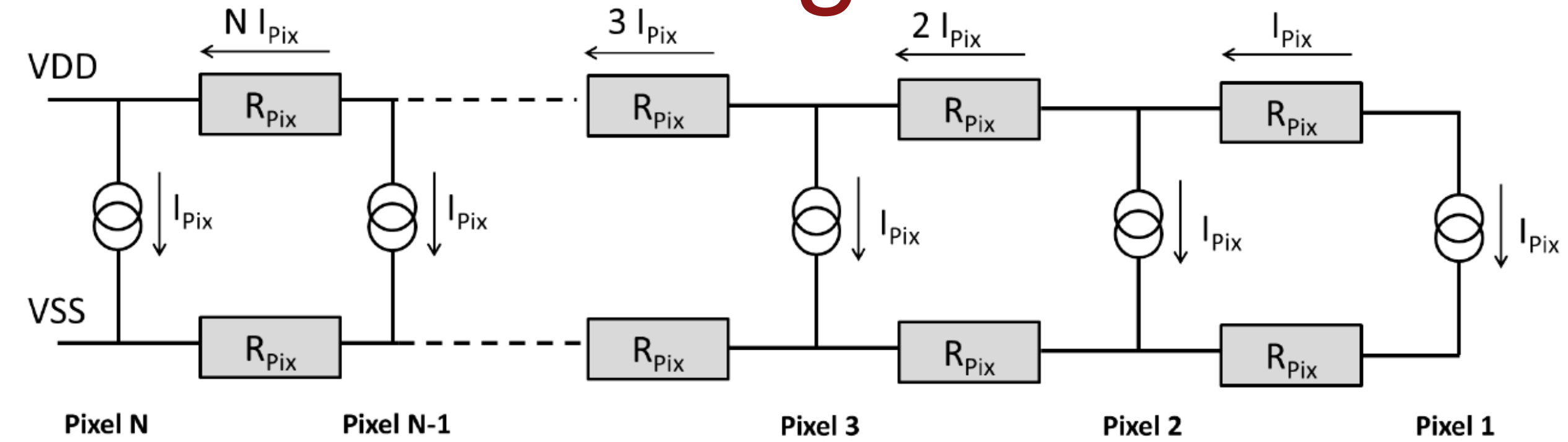
A column of 10 cm would have 4000 pixels

Double sided powering

→ max drop length = 2000 pixels

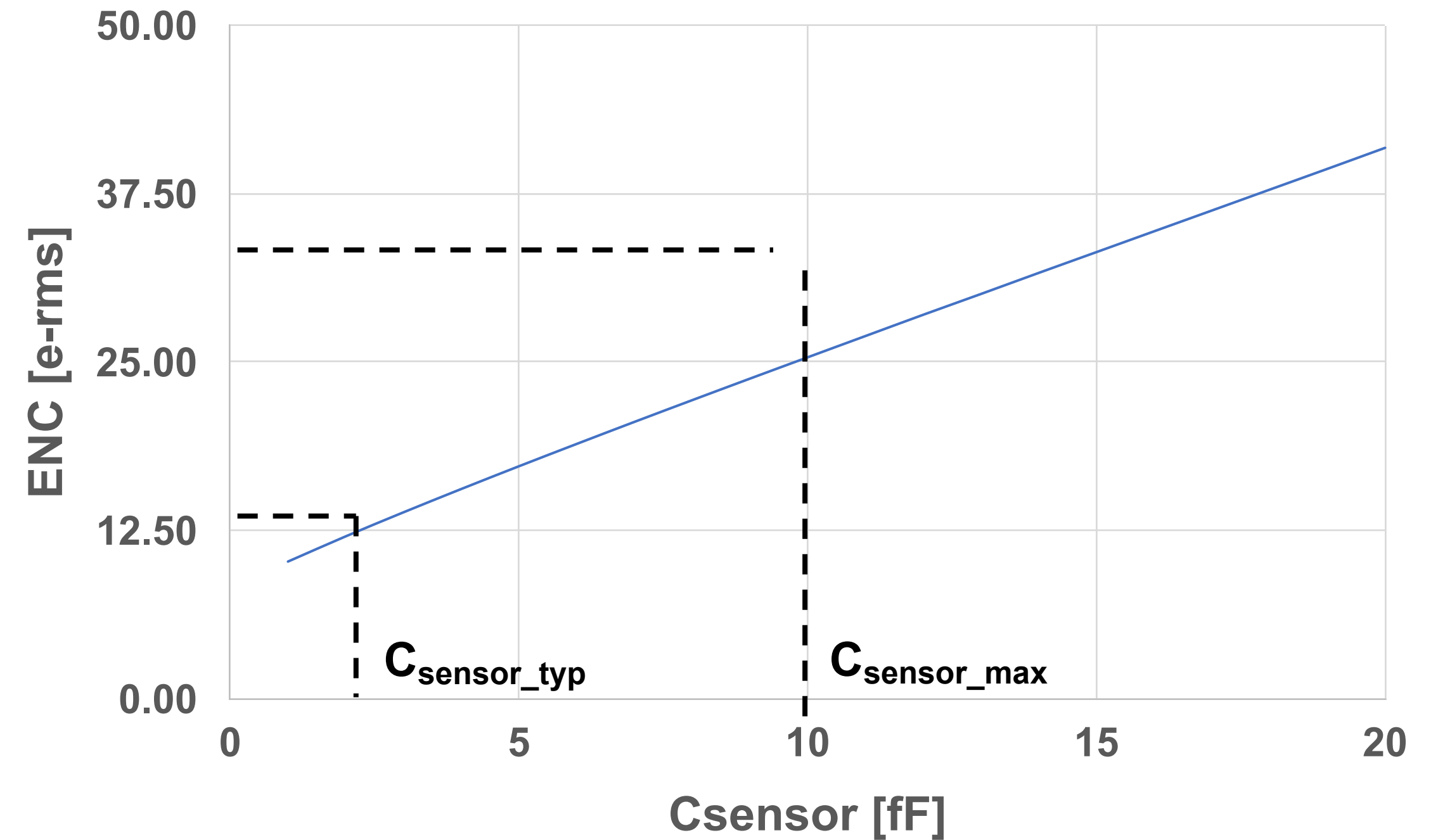
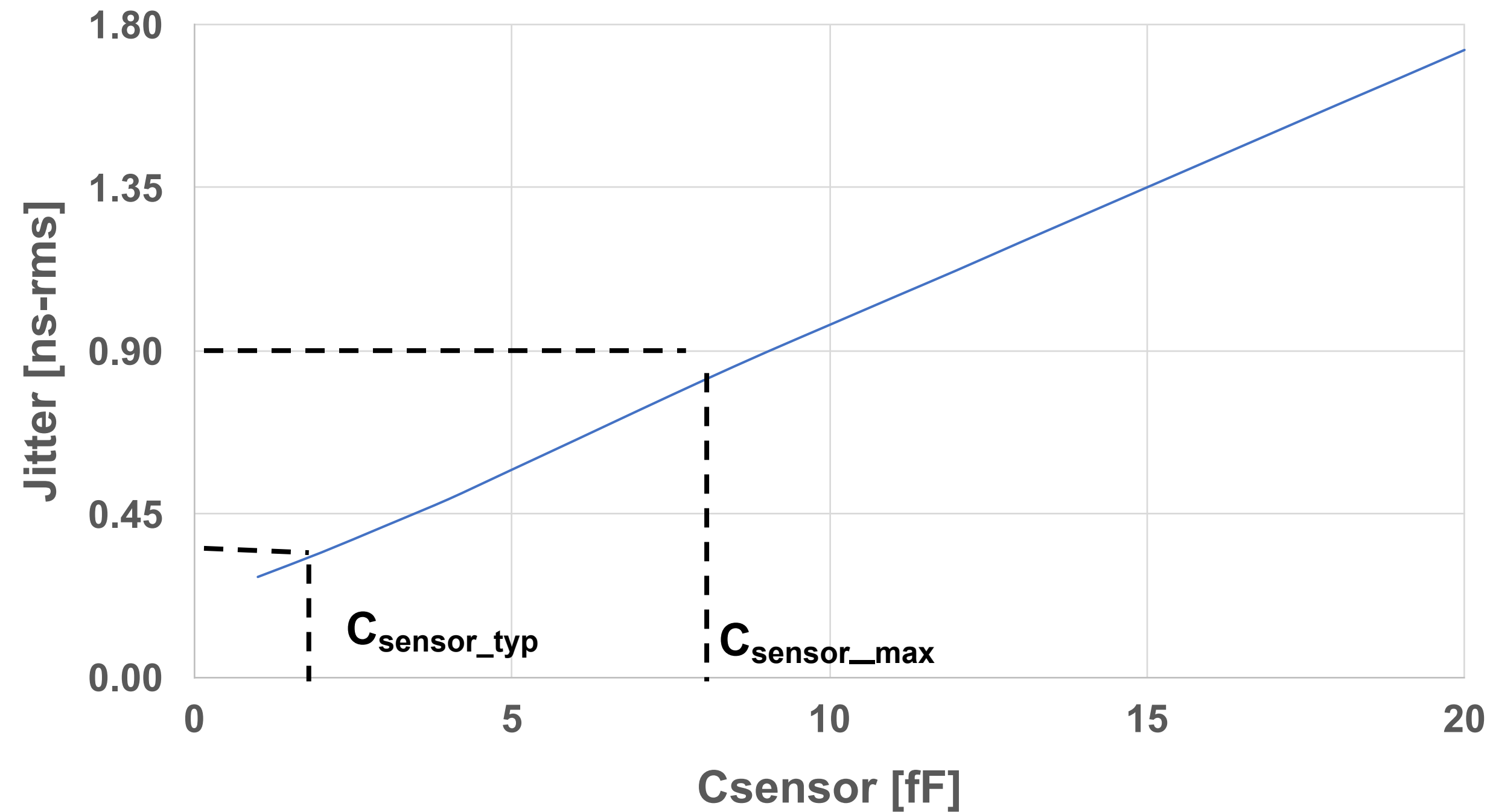
VDD-GND goes from 1.2 V near the power pads down to around 480 mV after 2000 pixels

The main limitation comes from large scale power distribution rather than cooling constraints



After  $10^3$  pixels (reticle, 2.5 cm),  $V_{drop} \approx 0.1 \text{ V}$   
 After  $4 \times 10^3$  pixels (sensor, 10cm),  $V_{drop} = 1.5 \text{ V} !$

# Simulation of Jitter and ENC as a Function of $C_{\text{sensor}}$



**jitter = 400 ps for  $C_{\text{sensor\_typ}} \approx 2$  fF**



**Ok for Specs**

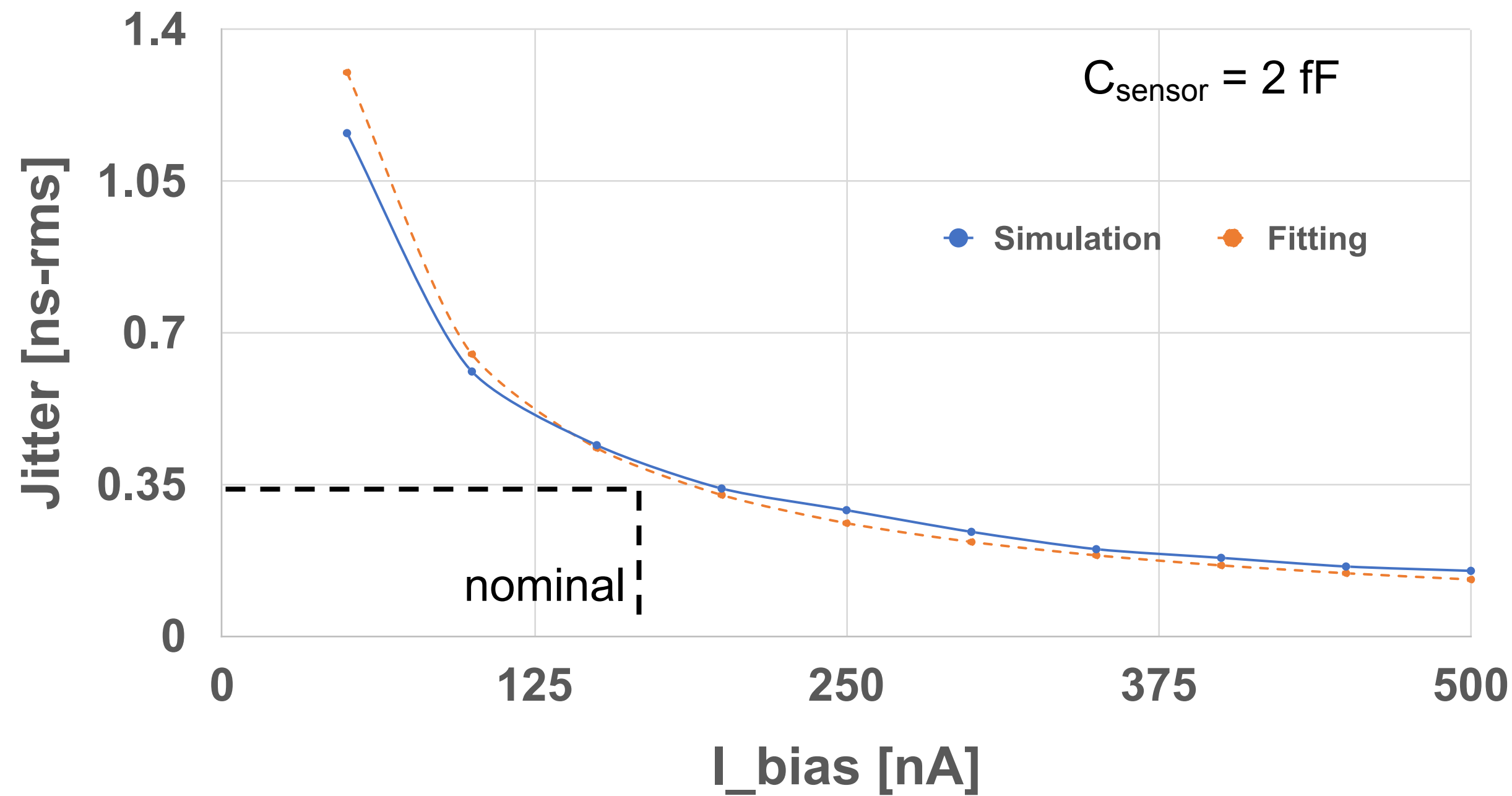


**ENC = 13 e-rms for  $C_{\text{sensor\_typ}} \approx 2$  fF**

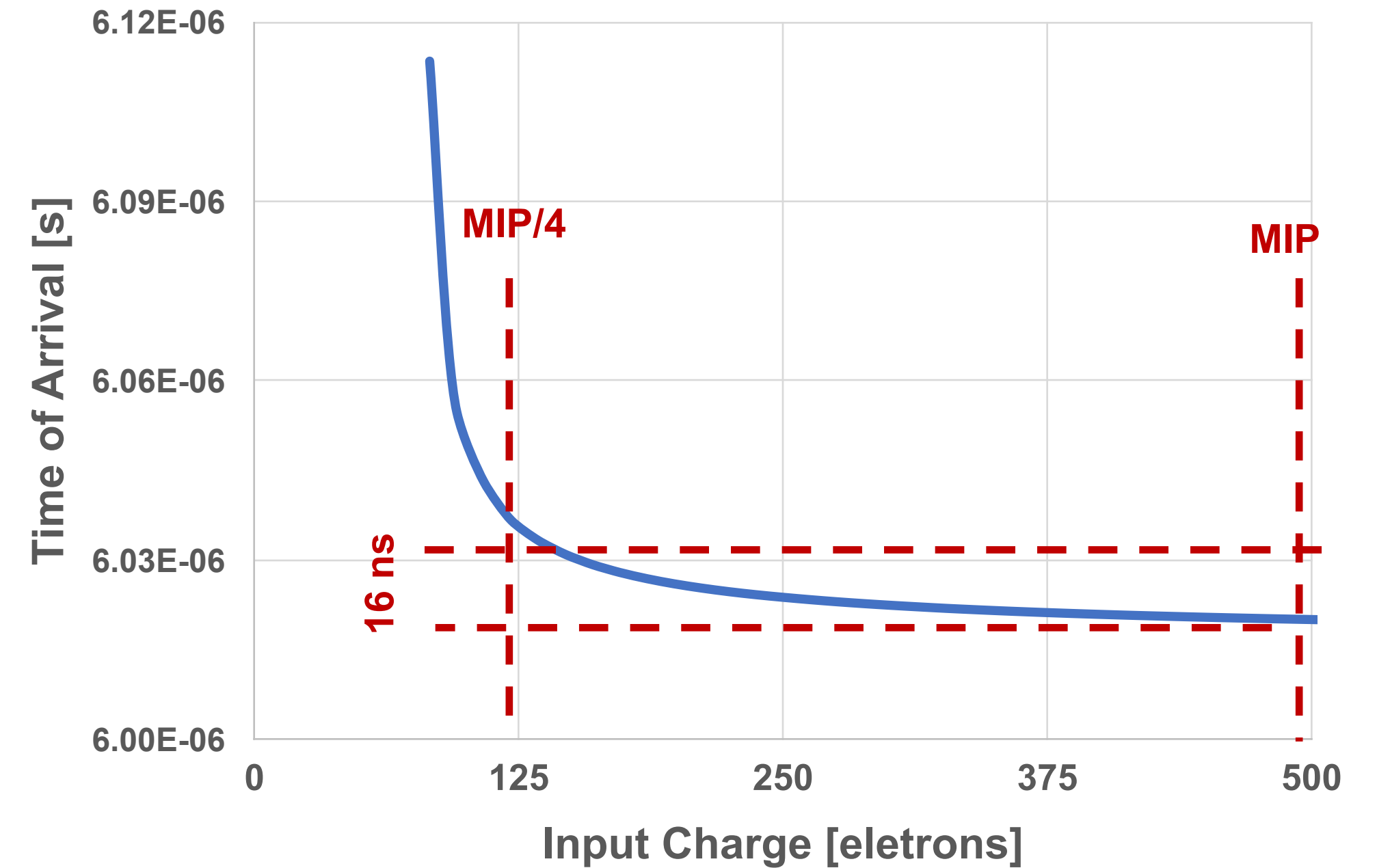
These simulations are with a nominal pixel current of 600 nA  $\rightarrow$   $\langle \text{Power density} \rangle = 115 \text{ mW/cm}^2 \times \text{duty cycle}$   
 For e<sup>+</sup>e<sup>-</sup> machines such as ILC and C<sup>3</sup>, duty cycle is expected < 1%

# Simulation Results : Jitter and Time Walk

## Jitter



## Time Walk



$I_{\text{bias}} = 200 \text{ nA} \equiv \text{pixel current} = 600 \text{ nA}$   
 From theory we expect :  $\sigma_{\text{FE}} \propto \frac{1}{(\text{Power})^{\frac{1}{n}}}$  with  $1 \leq n \leq 2$

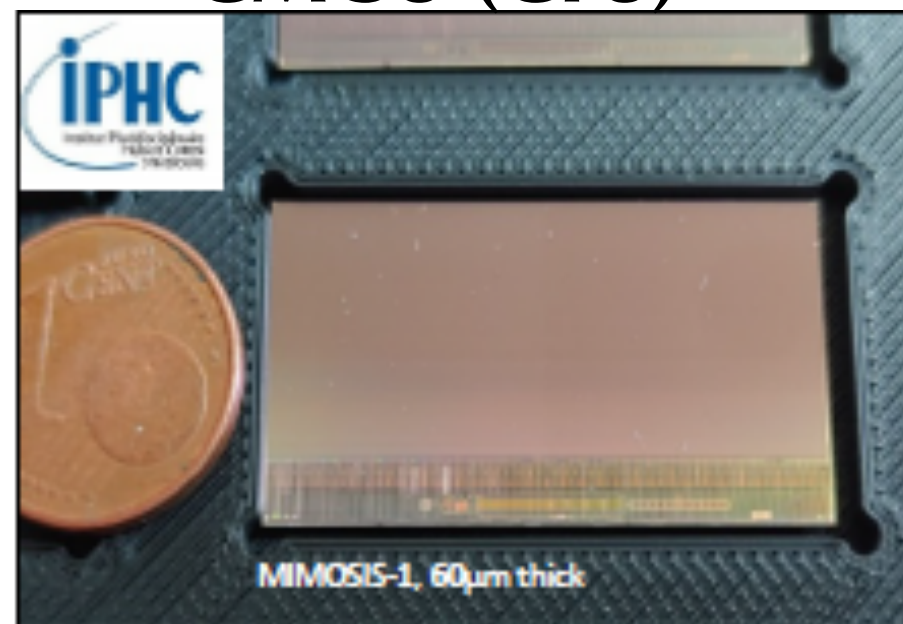
Time walk for MIP  $\rightarrow$  MIP/4 = 16 ns  
 Not negligible and must be corrected  
 (in pixel? In balcony? Offline? TBD)

# Sensors technology overview

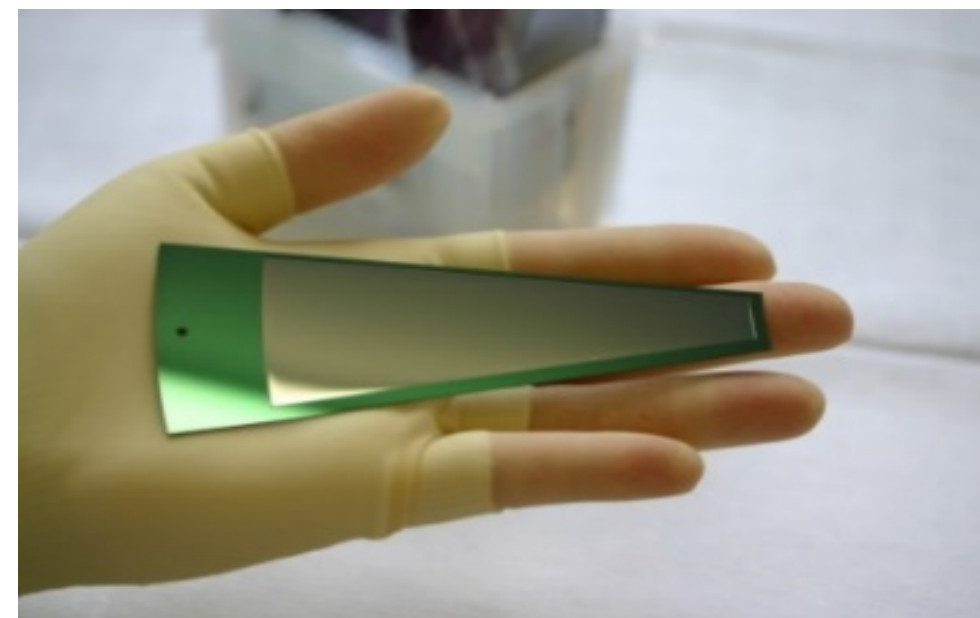
**Several possible choices** for the VTX detector:

- Monolithic Active Pixels (MAPS)
  - CMOS Pixel Sensors (CPS)
  - Fully Depleted on High Resistivity Substrate (DNwel sensing)
  - Fully Depleted SOI technologies
- Depleted Field Effect Transistors (DEPFET)
- Fine pixel Charged Coupled Devices (CCD)
- 3D integration
- The general landscape is also changing rapidly with advances in microelectronics

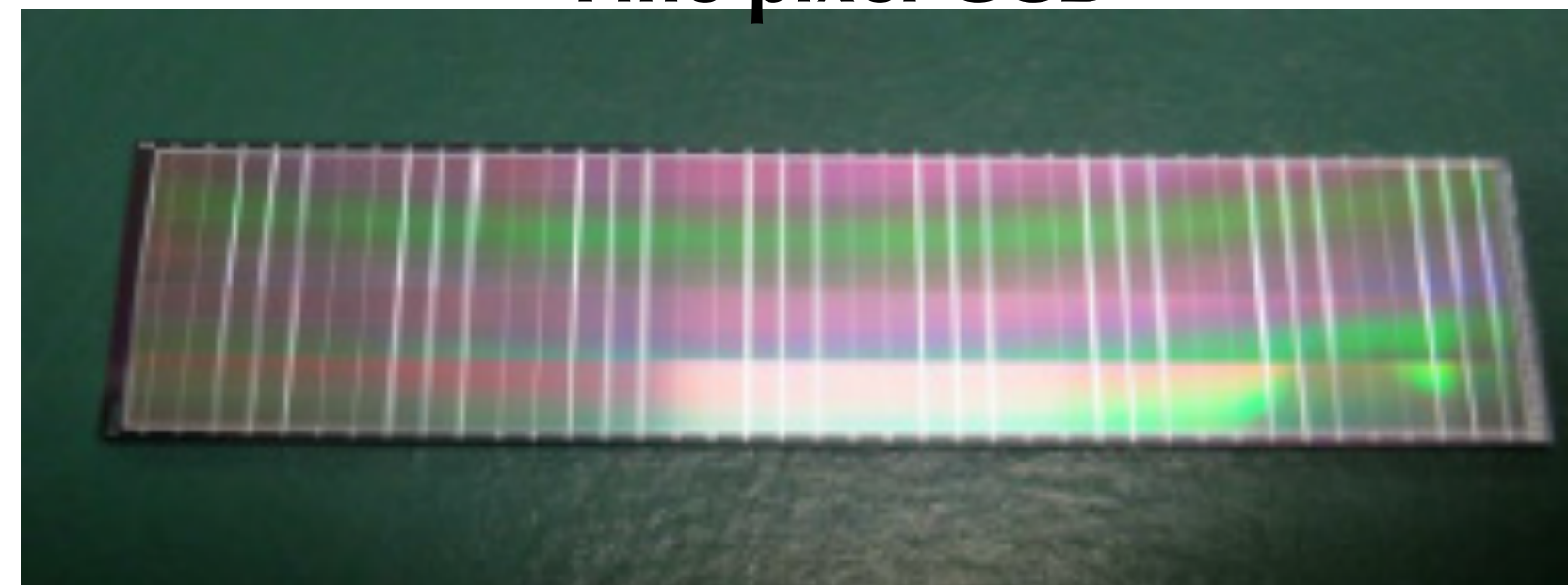
**CMOS (CPS)**



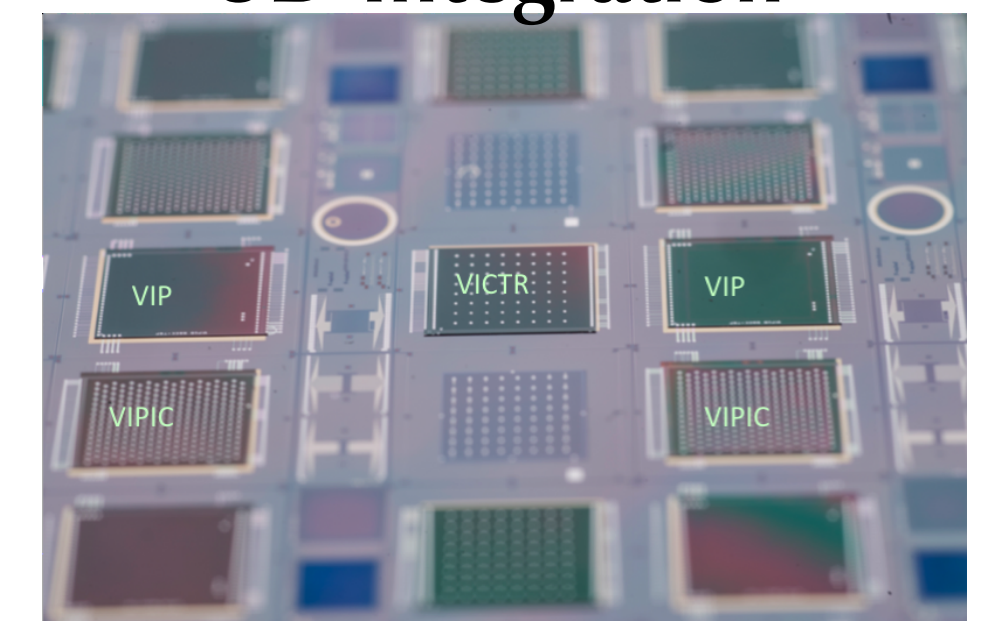
**DEPFET**



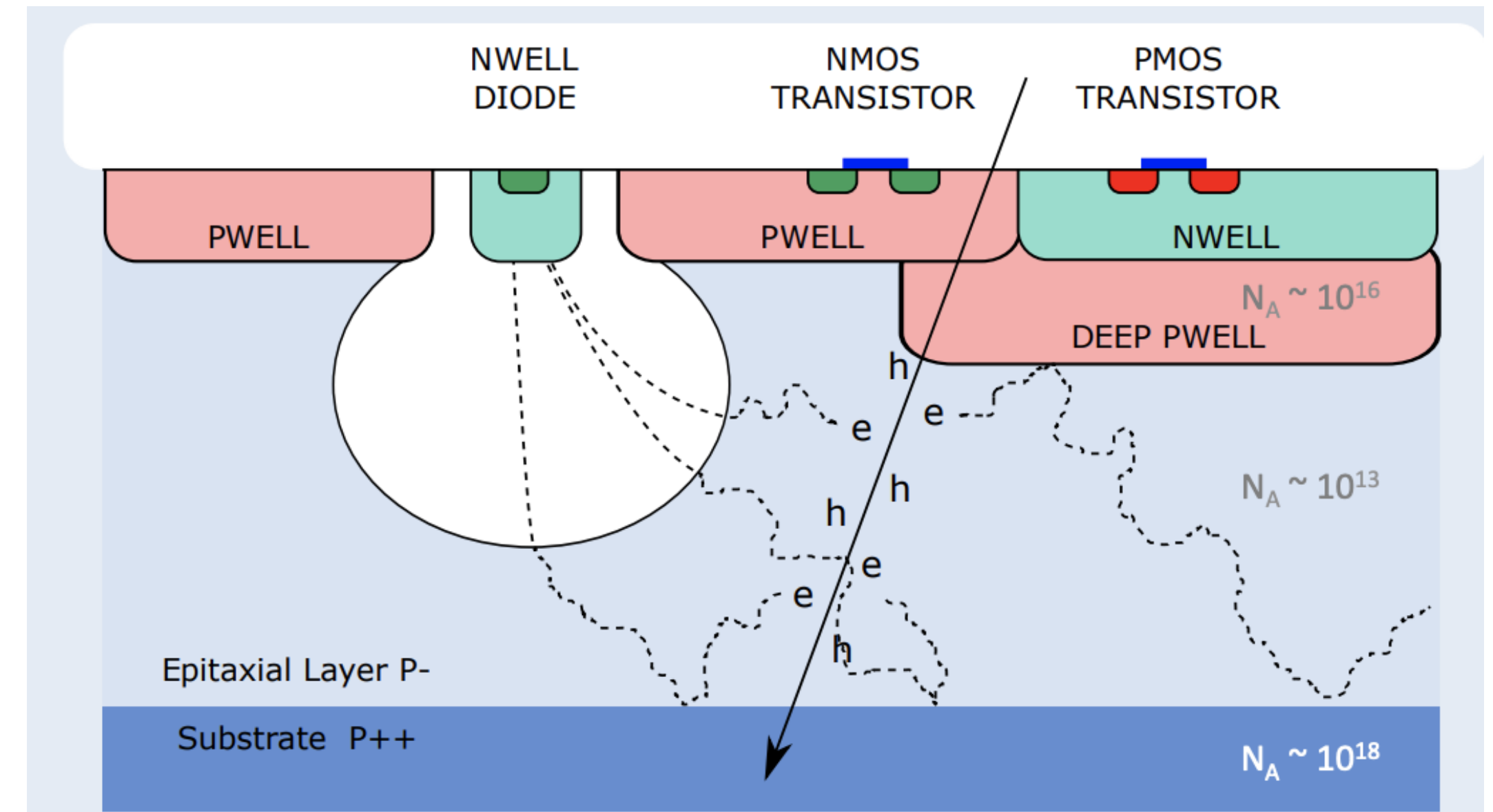
**Fine pixel CCD**



**3D Integration**



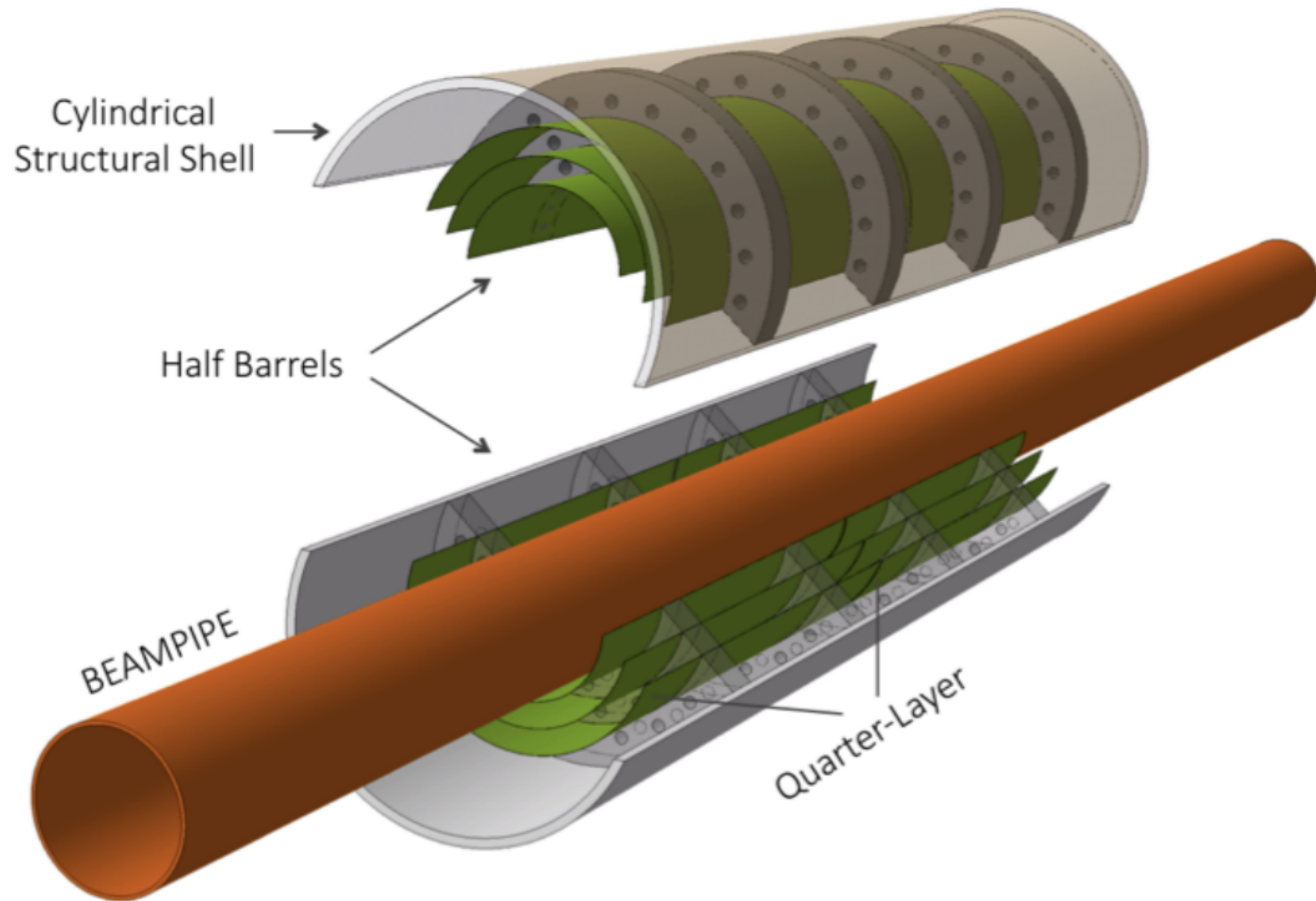
- With the current tracker upgrade ALICE redefined the new state-of-the-art in CMOS MAPS technology and its applications in HEP
- ALICE Pixel DEtector (ALPIDE) uses CMOS Pixel sensor used in imaging process
  - full CMOS circuitry within active area
  - Sensor thickness = 20-40  $\mu\text{m}$  (0.02-0.04% X0)
  - 5 $\mu\text{m}$  spatial resolution
  - radiation hard to  $10^{13}$  1 MeV  $n_{\text{eq}}$



V. Manzari, 2019

The used technology offers further opportunities: smaller feature size, **bending** that directly impact the key measurements that highly rely on precise vertexing and low material budget

# ALICE: Bent MAPS for Run 4



**Bending Si wafers + circuits is possible**

Recent ultra-thin wafer-scale silicon technologies allow:

Sensor thickness = 20-40  $\mu\text{m}$  - 0.02-0.04%  $X_0$

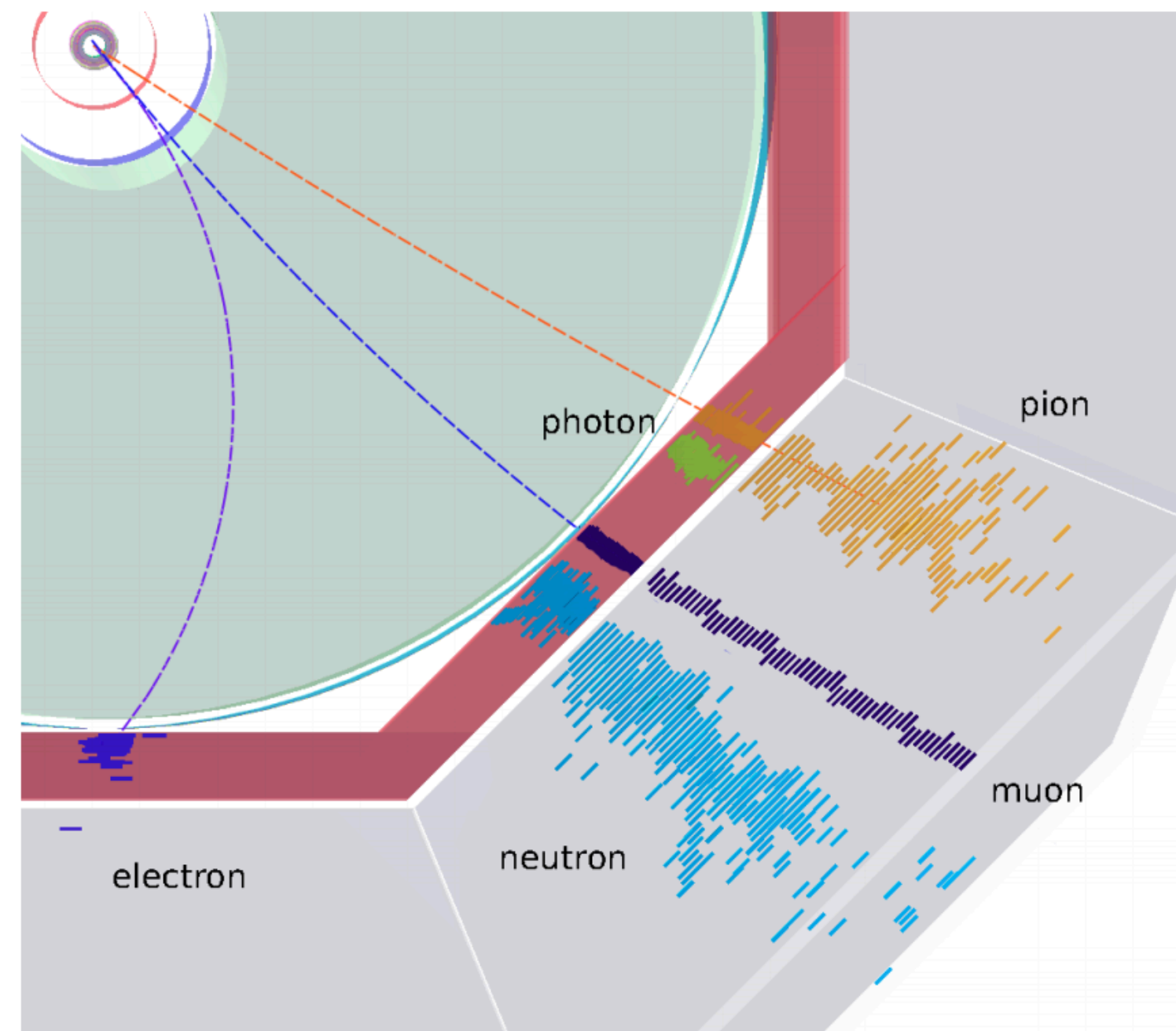
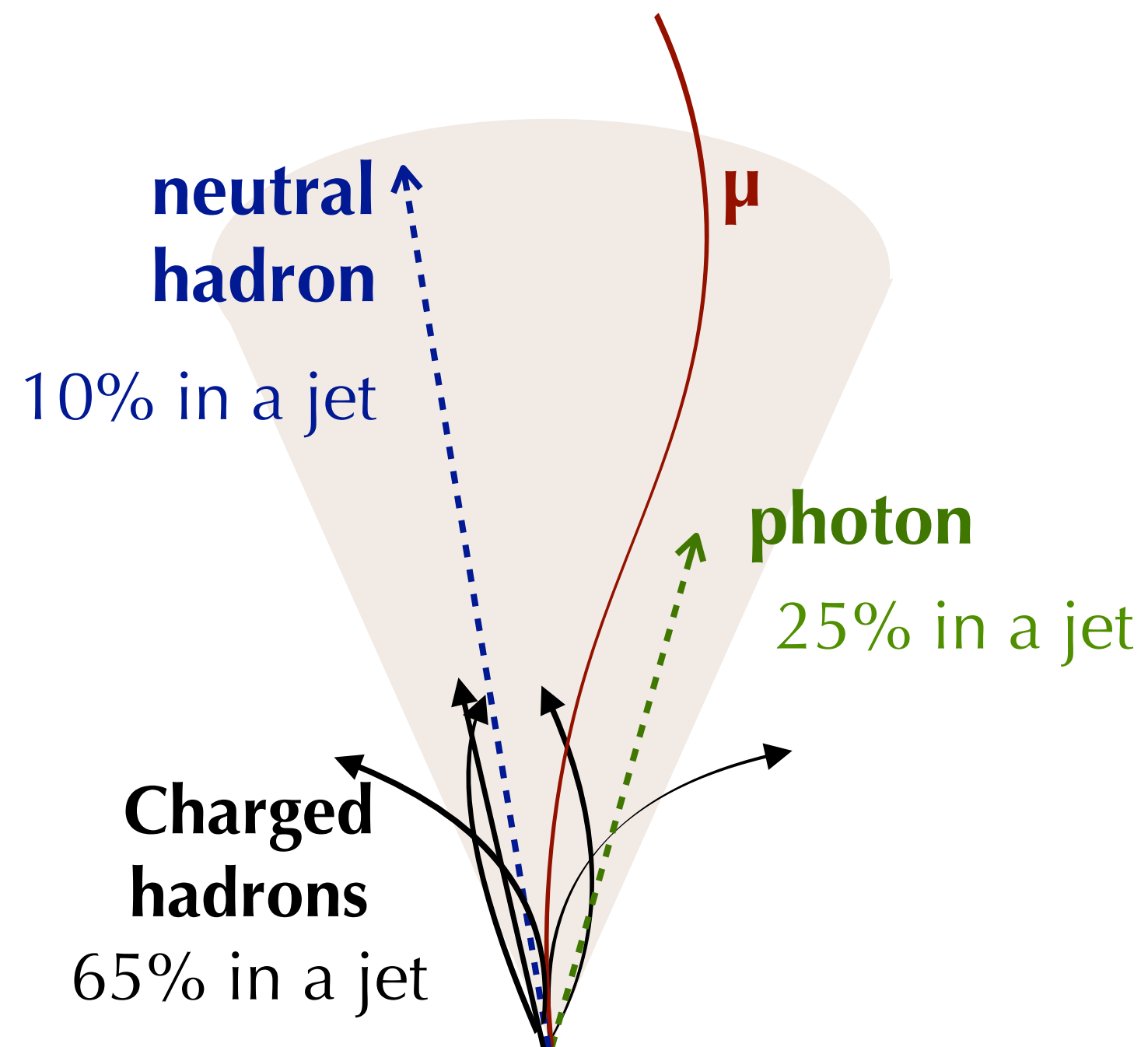
Sensors arranged with a perfectly cylindrical shape

a sensors thinned to  $\sim 30\mu\text{m}$  can be curved to a radius of 10-20mm (ALICE-PUBLIC-2018-013)

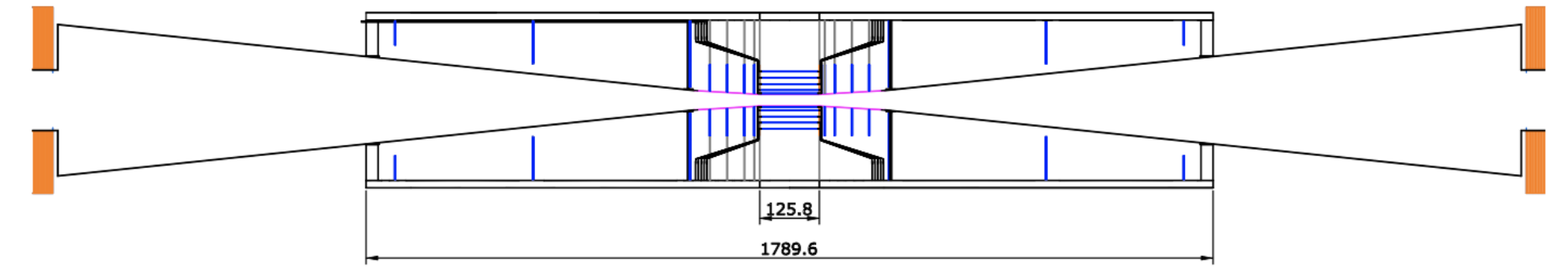
Industrial stitching & curved CPS along goals of ALICE-ITS3, possibly with 65 nm process

# Particle Flow Calorimeters

- CALICE collaboration: development and study of finely segmented and imaging calorimeters
  - Precise reconstruction of each particle within the jet
  - Issues: overlap between showers, complicated topology, separate physics event particles from beam-induced background
- CALICE R&D inspired CMS high granularity solution HGCal - Common test beams with the AHCAL prototype
  - New ideas/technologies being explored: high precision (ps) timing calorimeters and new sensors ideas (ex: MAPS, LGADs)



- Compact, cost constrained detector
  - 5 T solenoid B-field with  $R_{ECAL}=1.27$  m
  - All silicon pixel vertex + tracking system
  - Highly granular Si calorimeter optimized for PFLOW
- Pixel Vertex detector
  - 1 kGy and  $10^{11}$   $n_{eq}/cm^2$  per year
  - **Pixel hit resolution** better than  $5 \mu m$  in barrel
    - Better if charge sharing is used
  - Less than **0.3%  $X_0$**  per pixel layer
  - air cooling  $\rightarrow$  low-mass sensor
  - Single bunch time resolution
    - Low capacitance and high S/N allows for acceptable power dissipation for single-crossing time resolution ( $\sim 300-700$  ns)
- Outer pixel Tracker:
  - 0.1-0.15%  $X_0$  in the central region



Barrel	R	$z_{max}$
Layer 1	14	63
Layer 2	22	63
Layer 3	35	63
Layer 4	48	63
Layer 5	60	63

Disk	$R_{inner}$	$R_{outer}$	$z_{center}$
Disk 1	14	71	72
Disk 2	16	71	92
Disk 3	18	71	123
Disk 4	20	71	172

Forward Disk	$R_{inner}$	$R_{outer}$	$z_{center}$
Disk 1	28	166	207
Disk 2	76	166	541
Disk 3	117	166	832

20x20  $\mu m$  pixels in the central region  
 50x50  $\mu m$  for the forward tracker disks

